

Title: METHODS OF NANOSTRUCTURE FORMATION AND SHAPE SELECTION

Inventors: Younan Xia and Yugan Sun

Docket No.: 53433/2 Serial No.: 10/732,910 Filed: 12/09/2003

REPLACEMENT SHEET (Set A)

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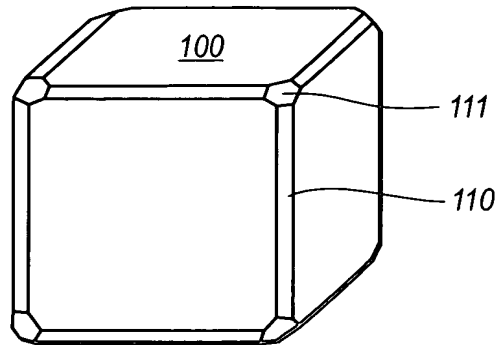


Fig. 1

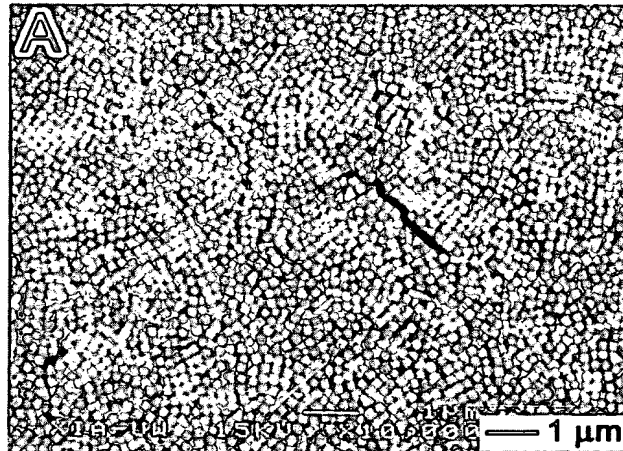


Fig. 2A

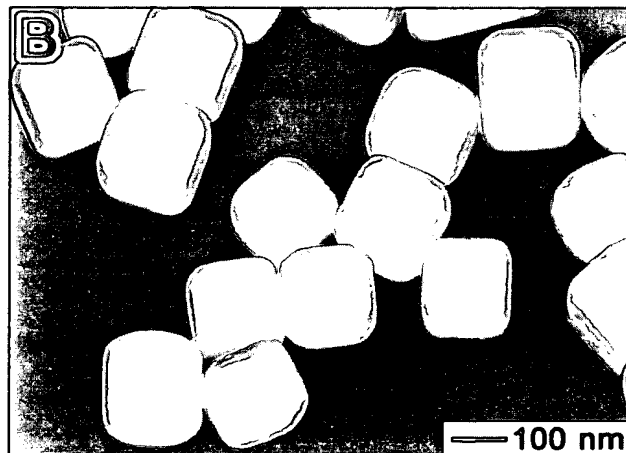
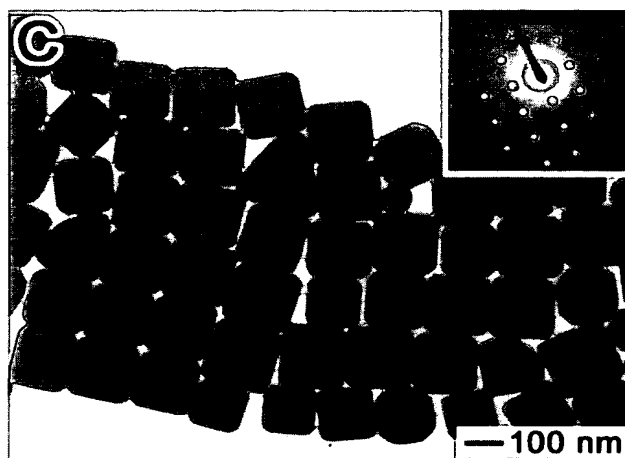
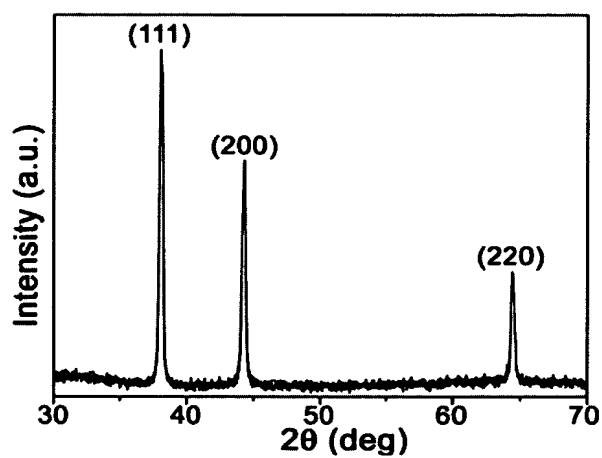


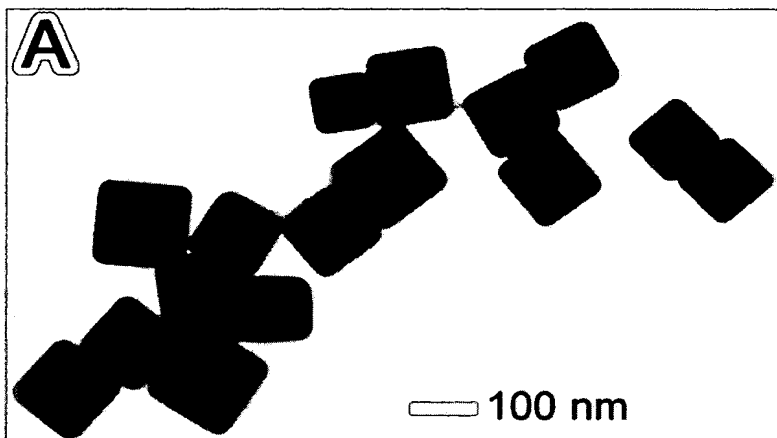
Fig. 2B



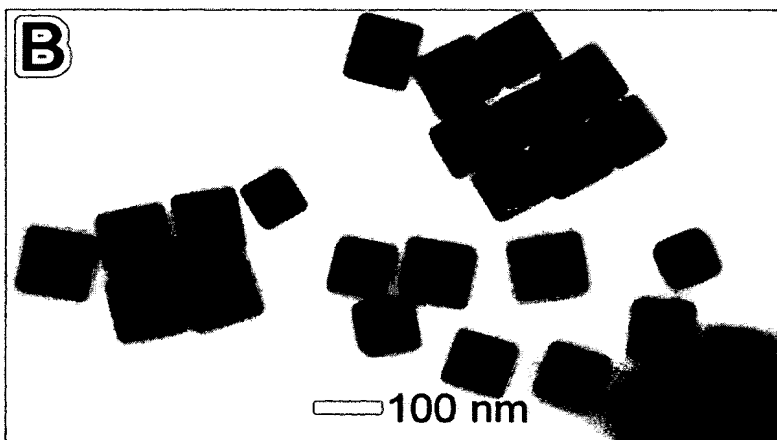
*Fig. 2C*



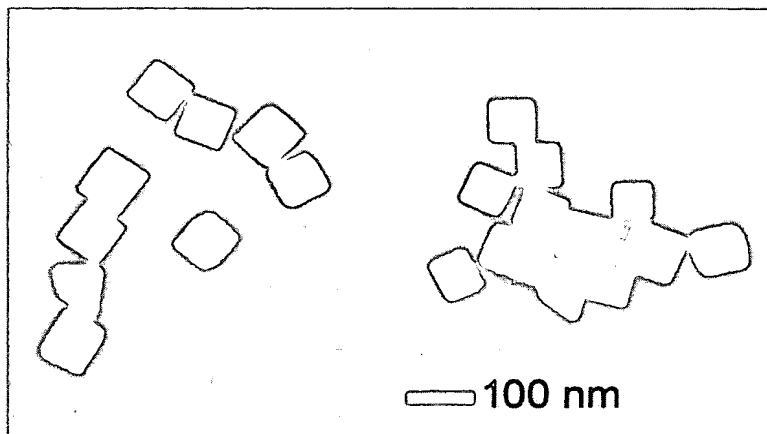
*Fig. 2D*



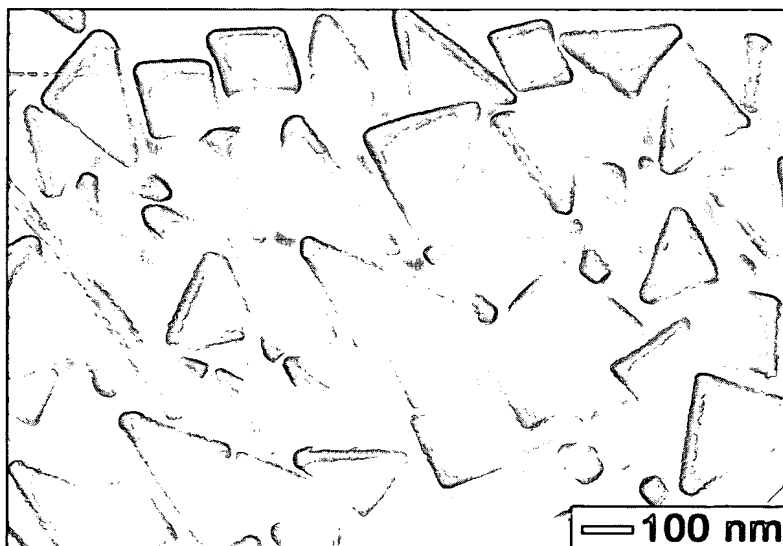
*Fig. 3A*



*Fig. 3B*



*Fig. 4*



*Fig. 5*

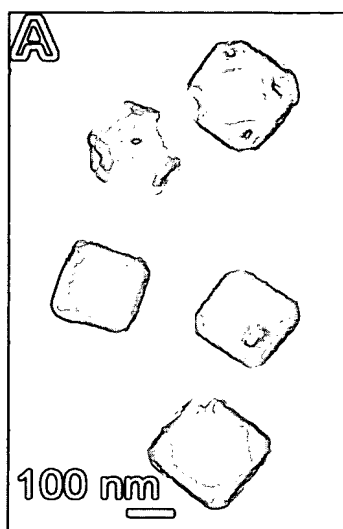


Fig. 6A

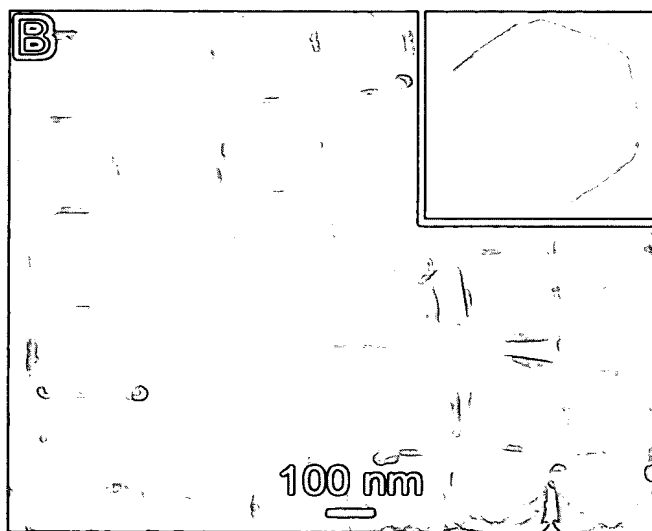


Fig. 6B

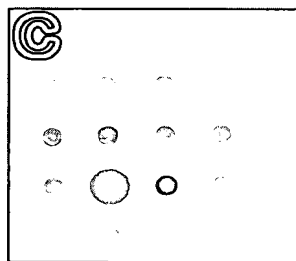


Fig. 6C

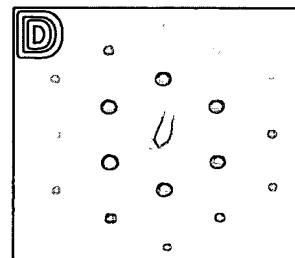


Fig. 6D

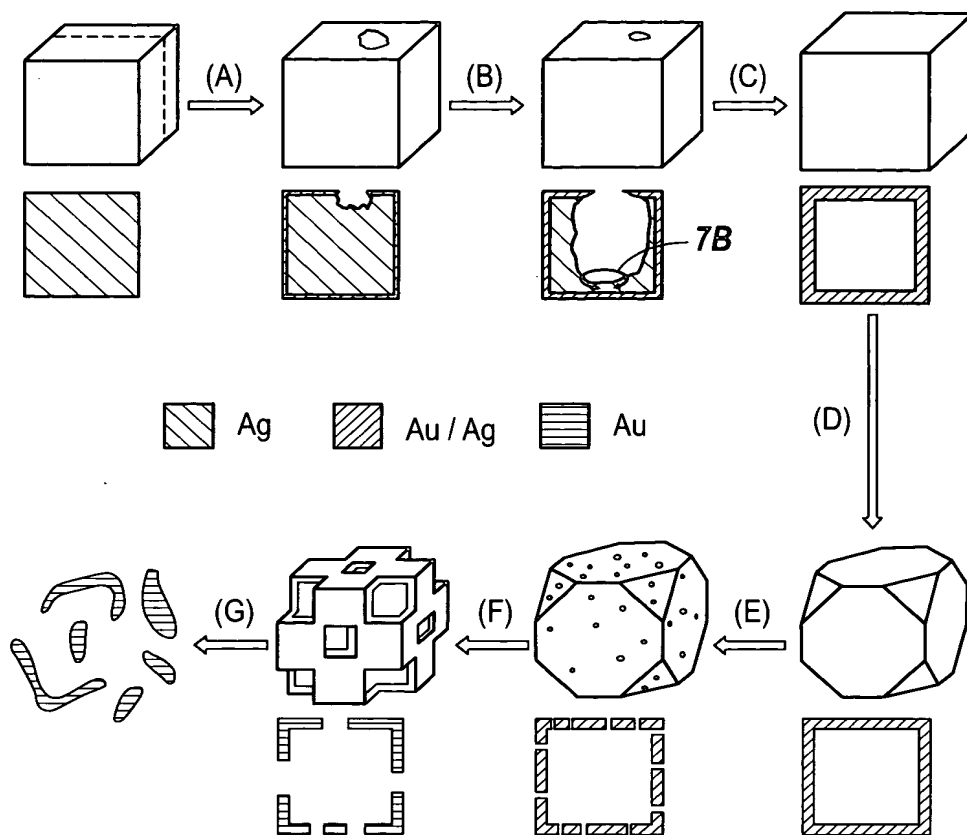


Fig. 7A

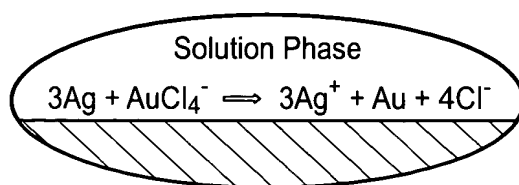


Fig. 7B

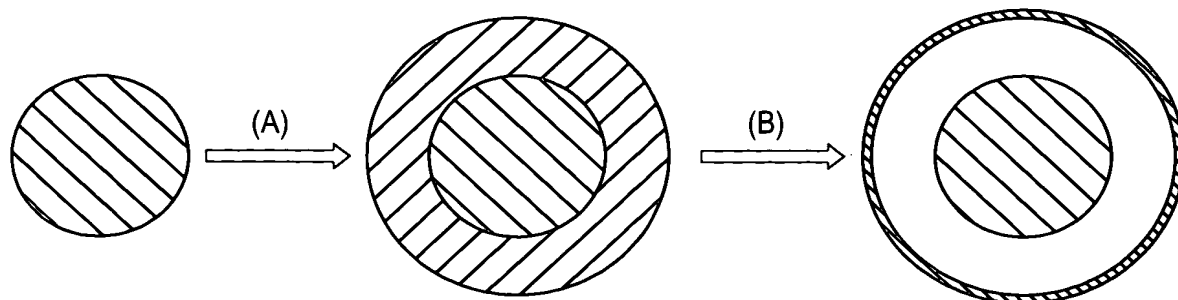
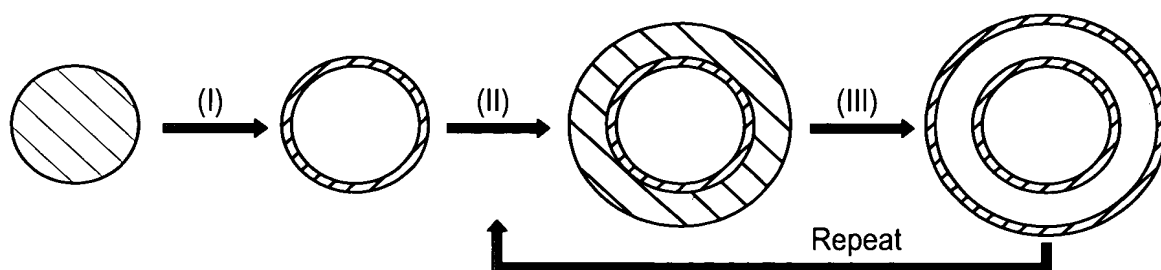
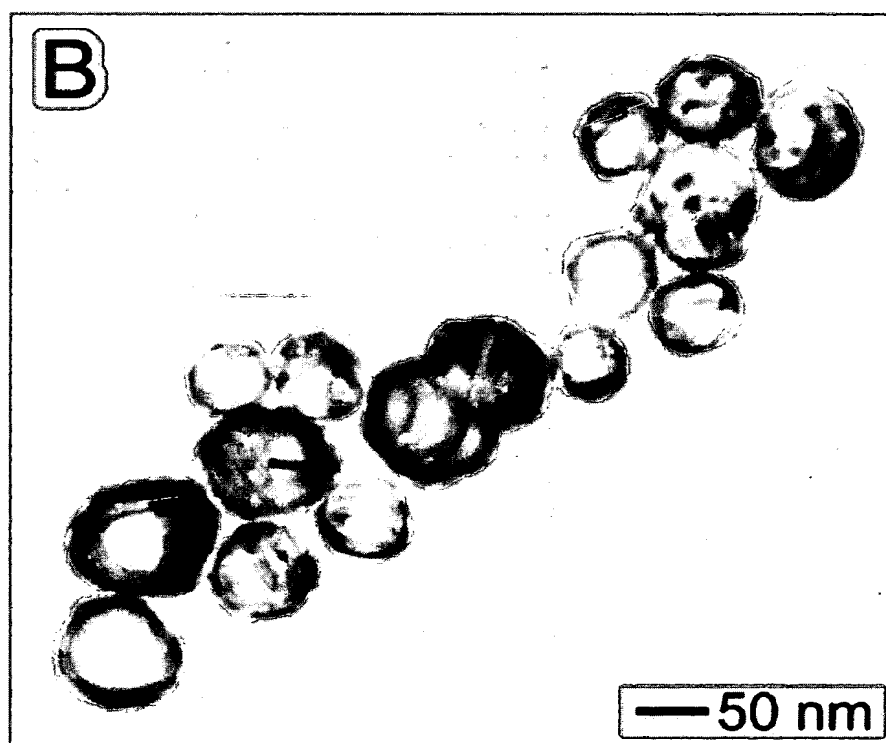


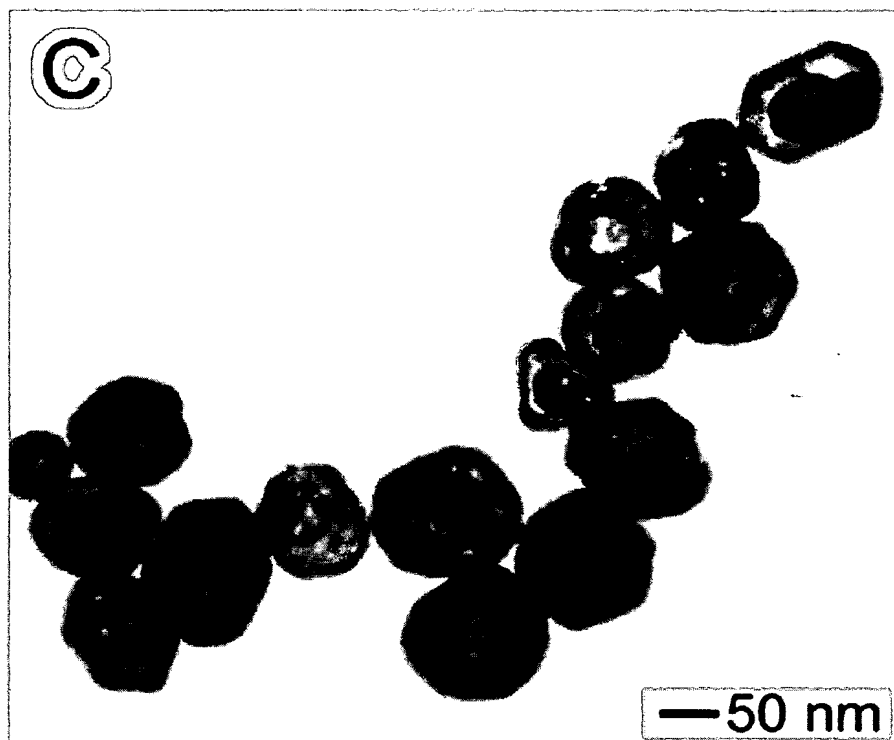
Fig. 8



**Fig. 9A**



**Fig. 9B**



*Fig. 9C*



*Fig. 9D*

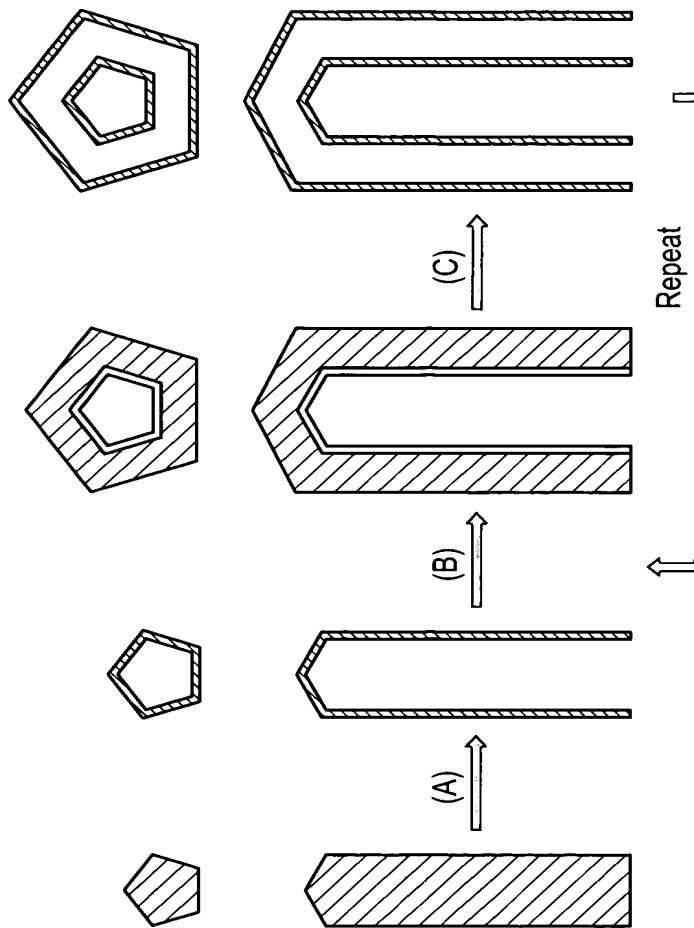
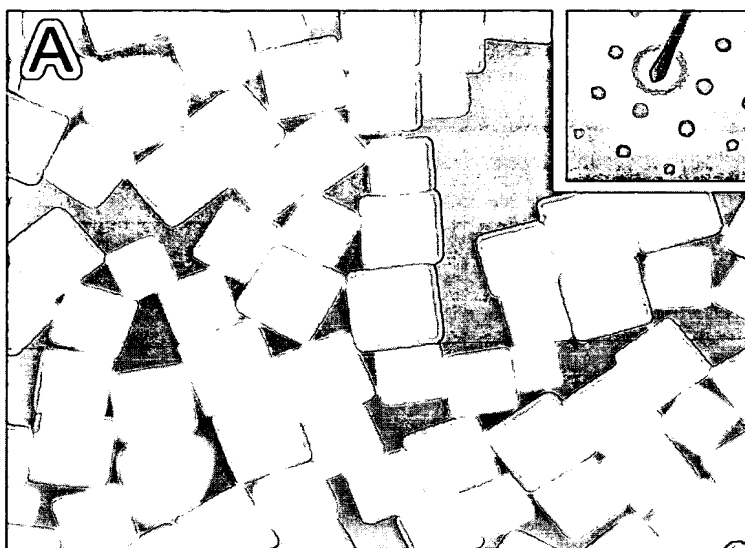
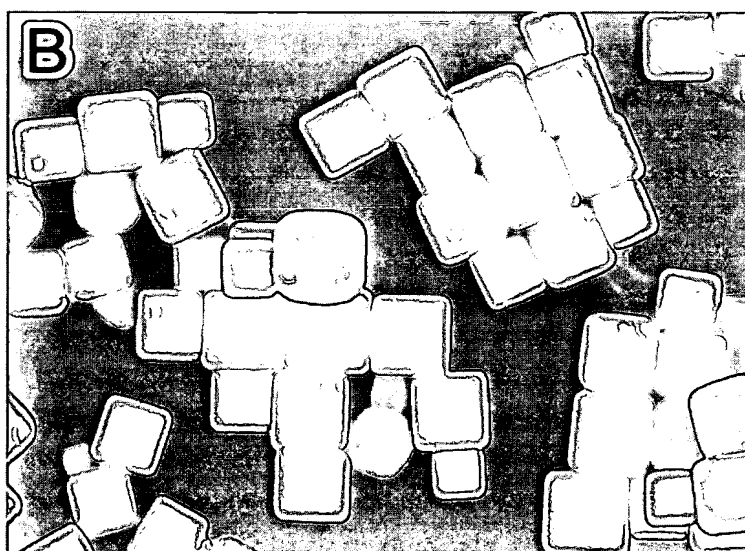


Fig. 10



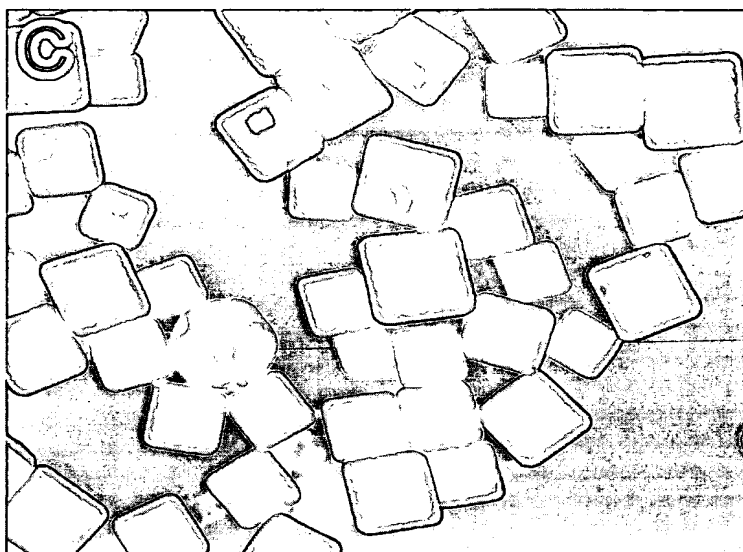
—100 nm

*Fig. 11A*



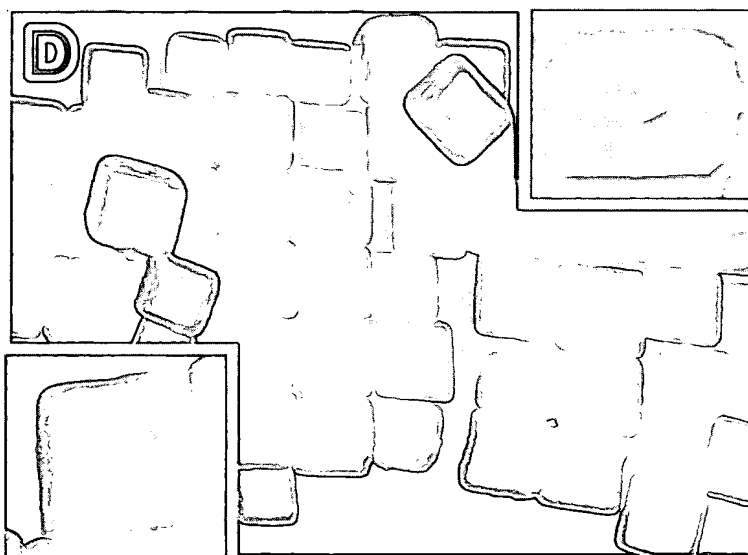
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*Fig. 11B*



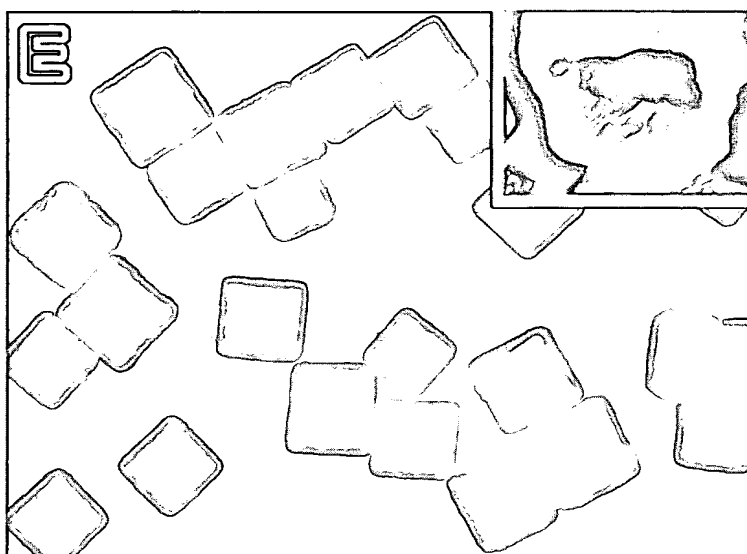
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*Fig. 11C*



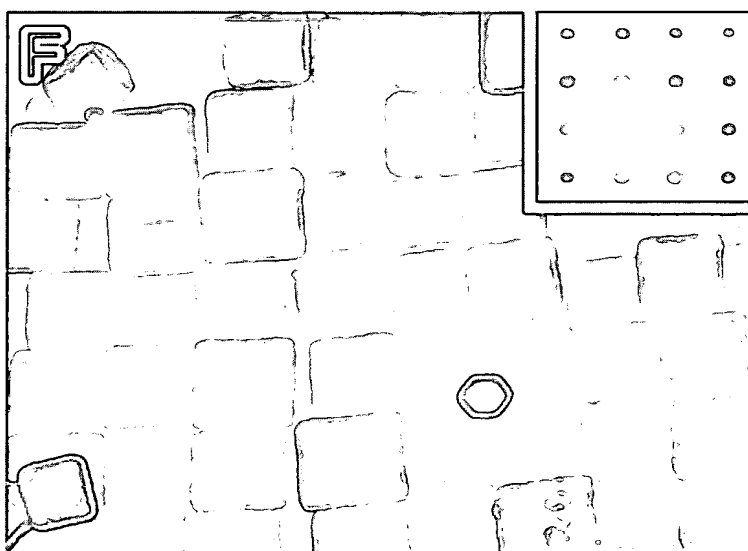
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*Fig. 11D*



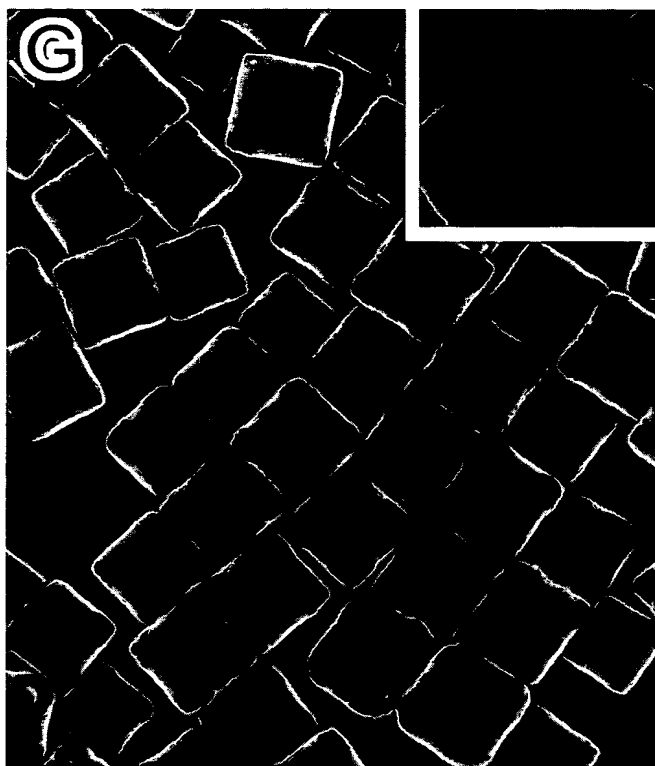
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*Fig. 11E*



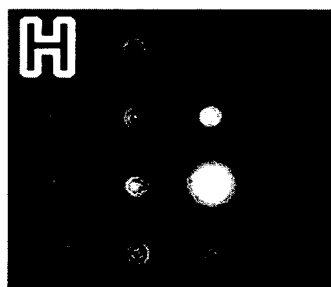
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*Fig. 11F*



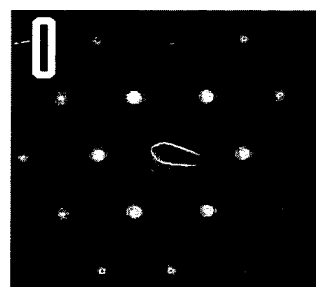
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*Fig. 11G*



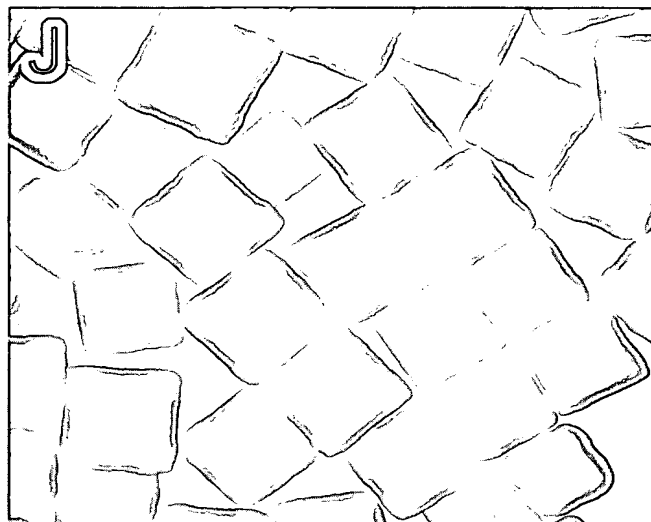
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*Fig. 11H*



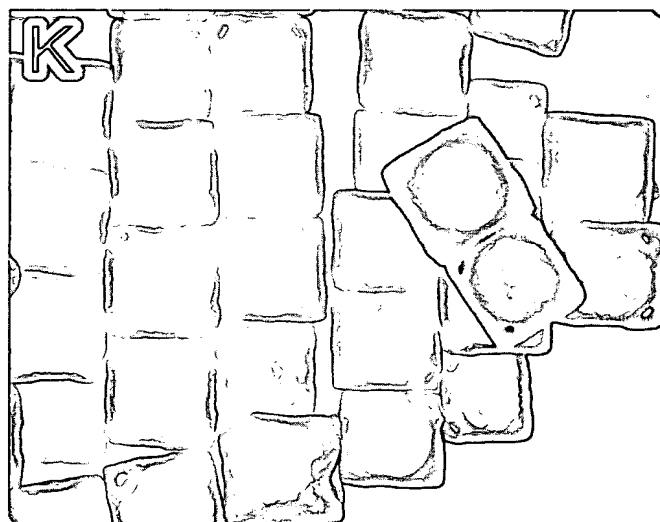
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*Fig. 11I*



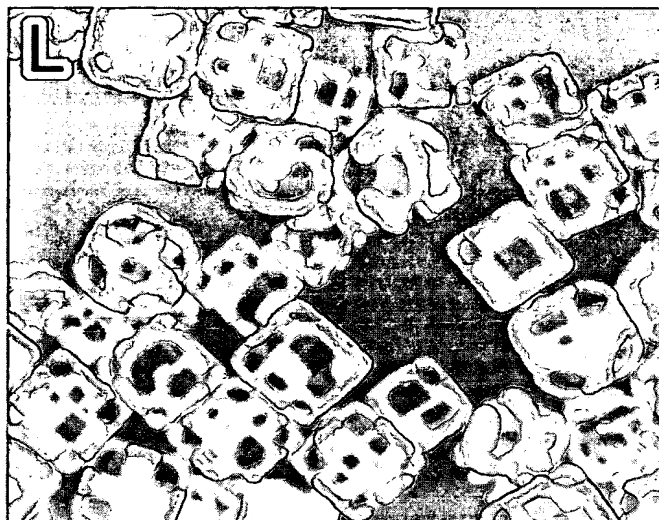
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*Fig. 11J*



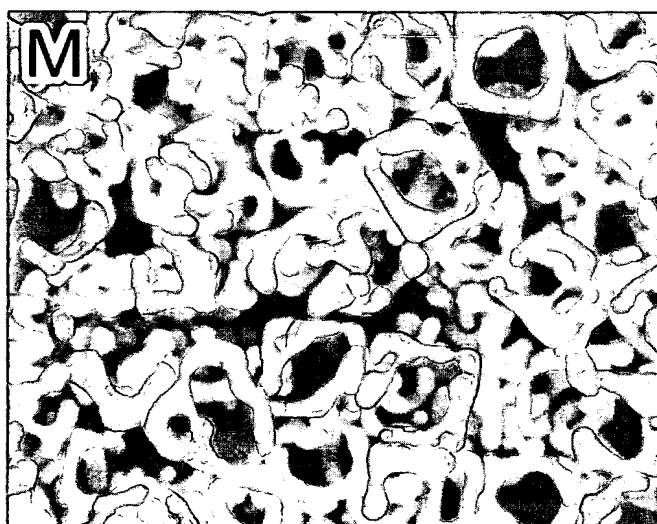
—100 nm

*Fig. 11K*



—100 nm

*Fig. 11L*



—100 nm

*Fig. 11M*

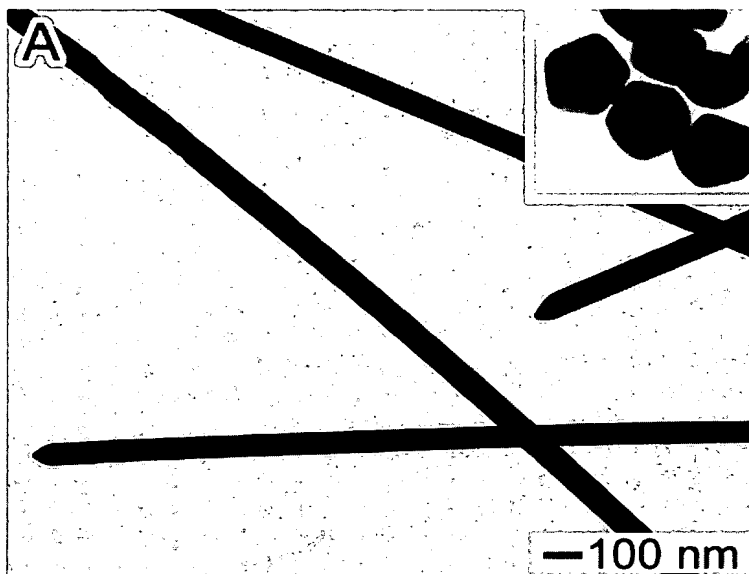


Fig. 12A

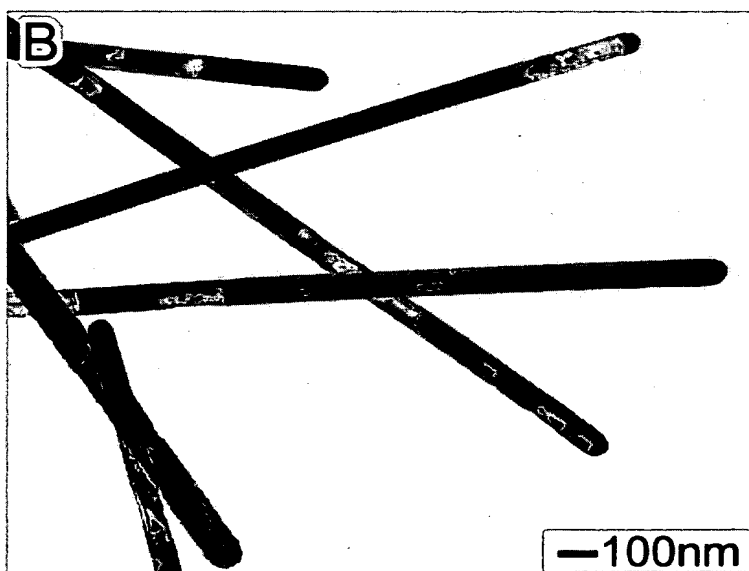
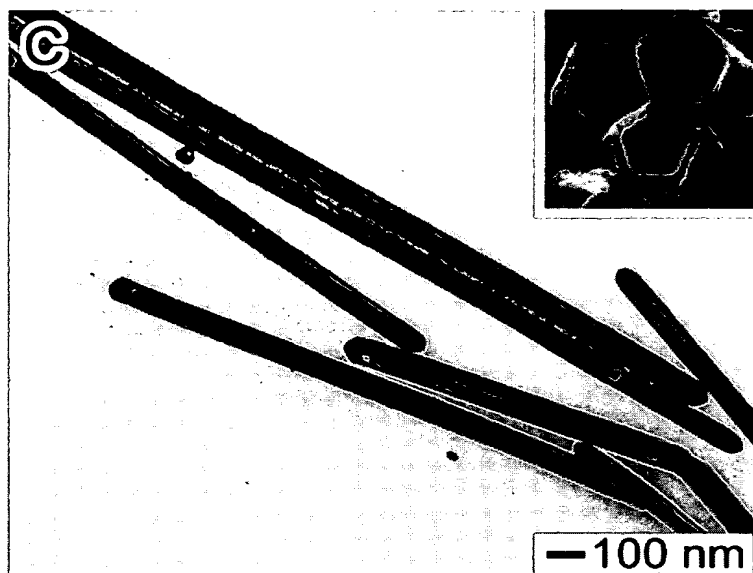
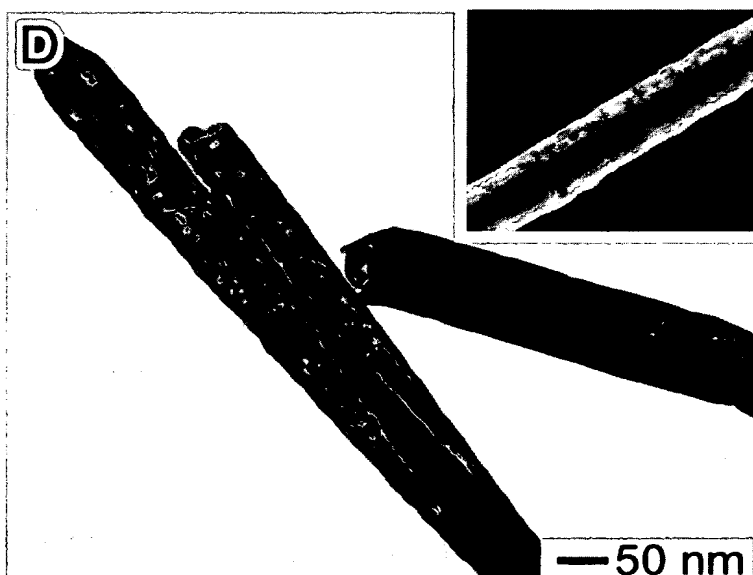


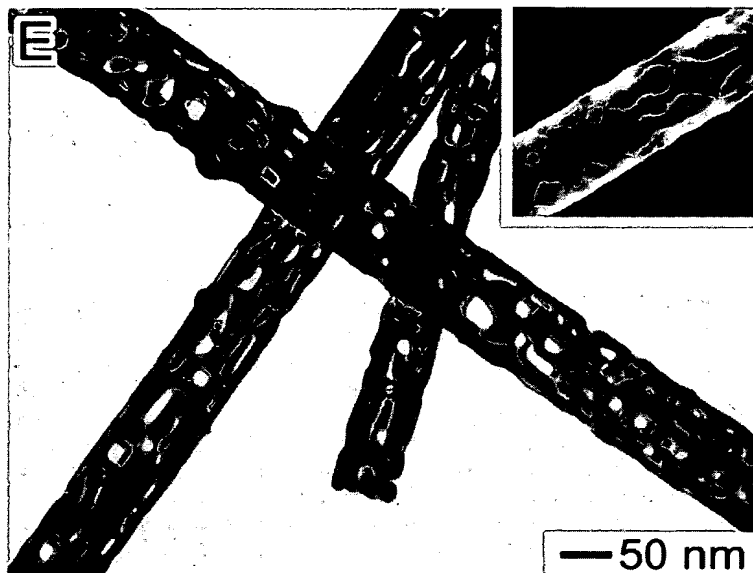
Fig. 12B



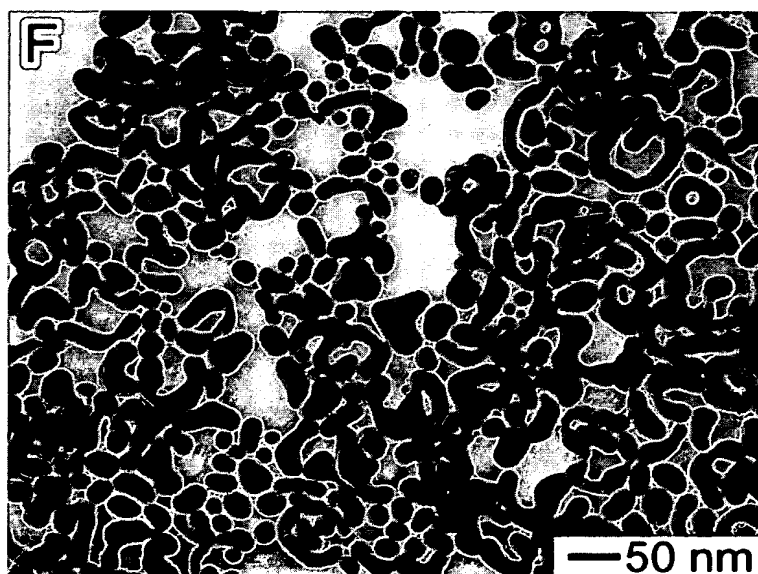
*Fig. 12C*



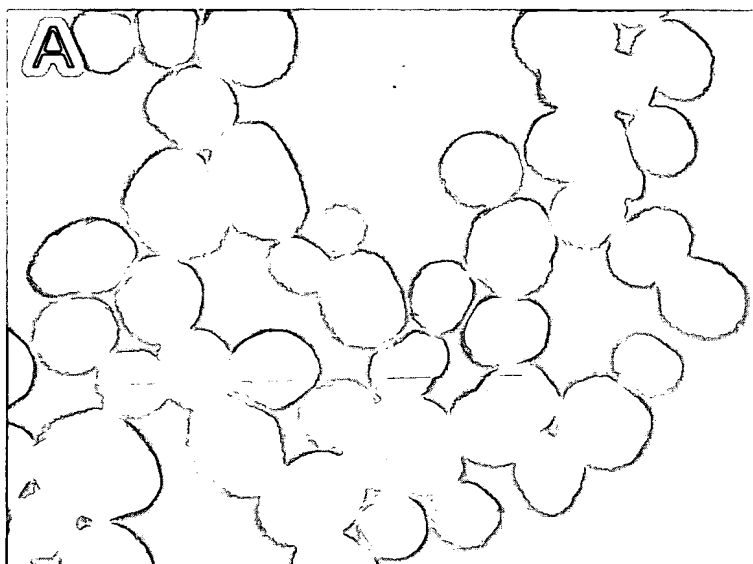
*Fig. 12D*



*Fig. 12E*

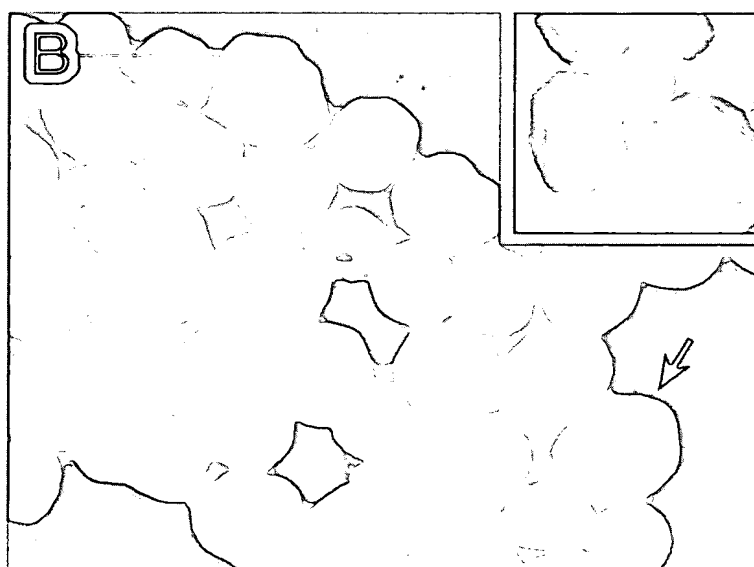


*Fig. 12F*



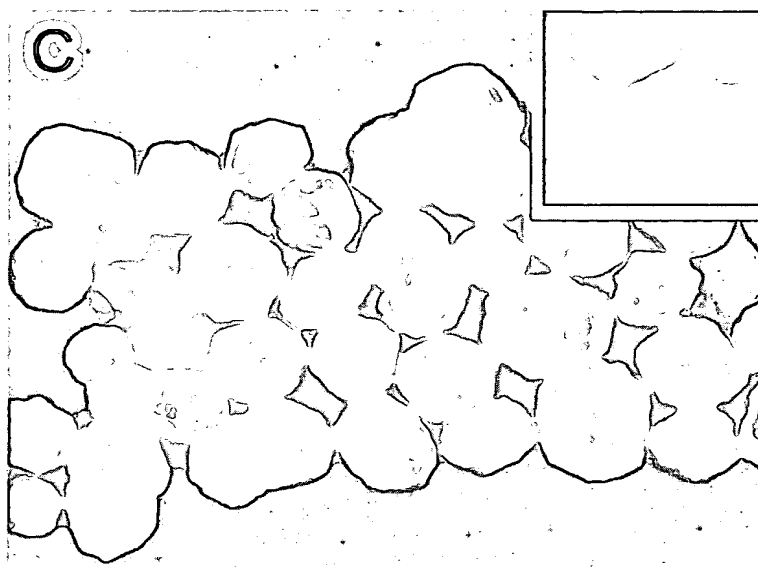
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*Fig. 13A*



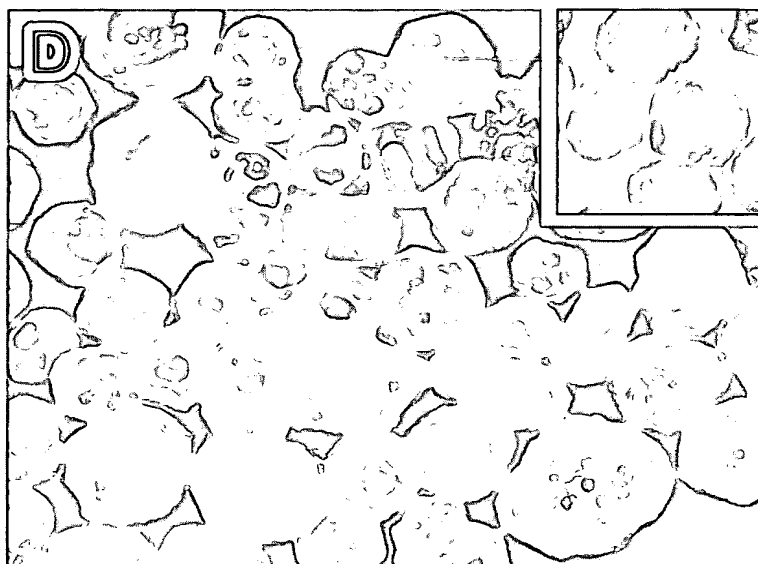
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*Fig. 13B*



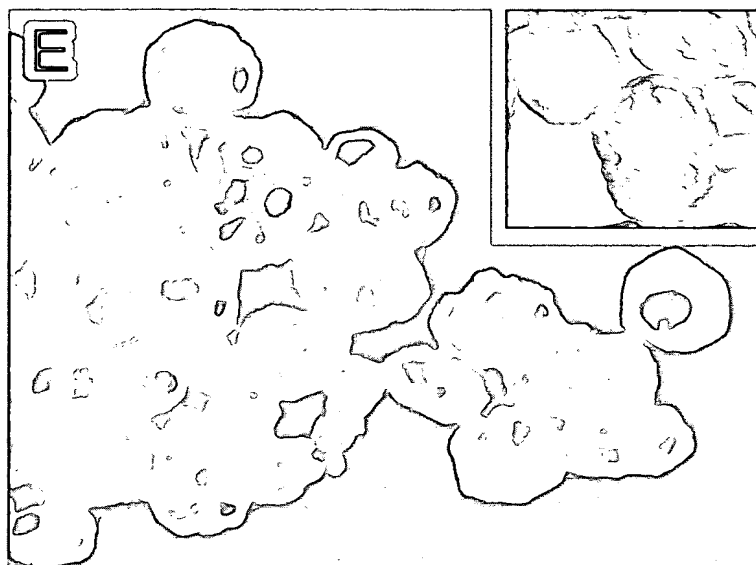
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*Fig. 13C*



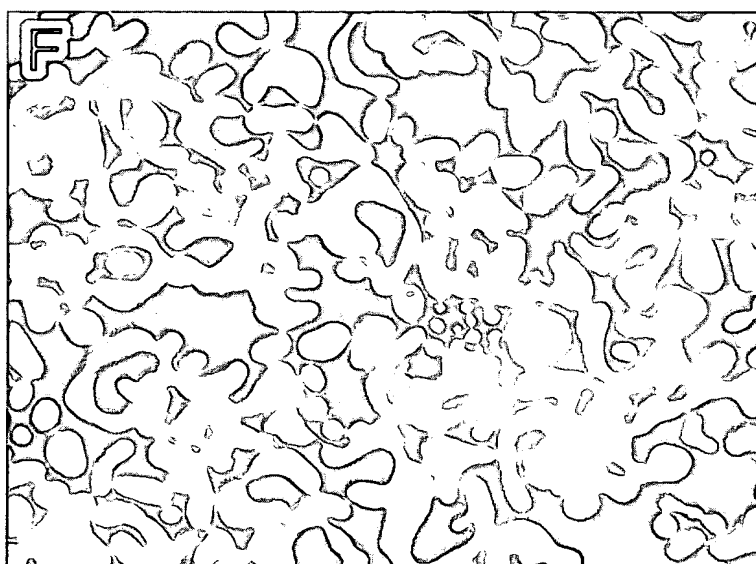
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*Fig. 13D*



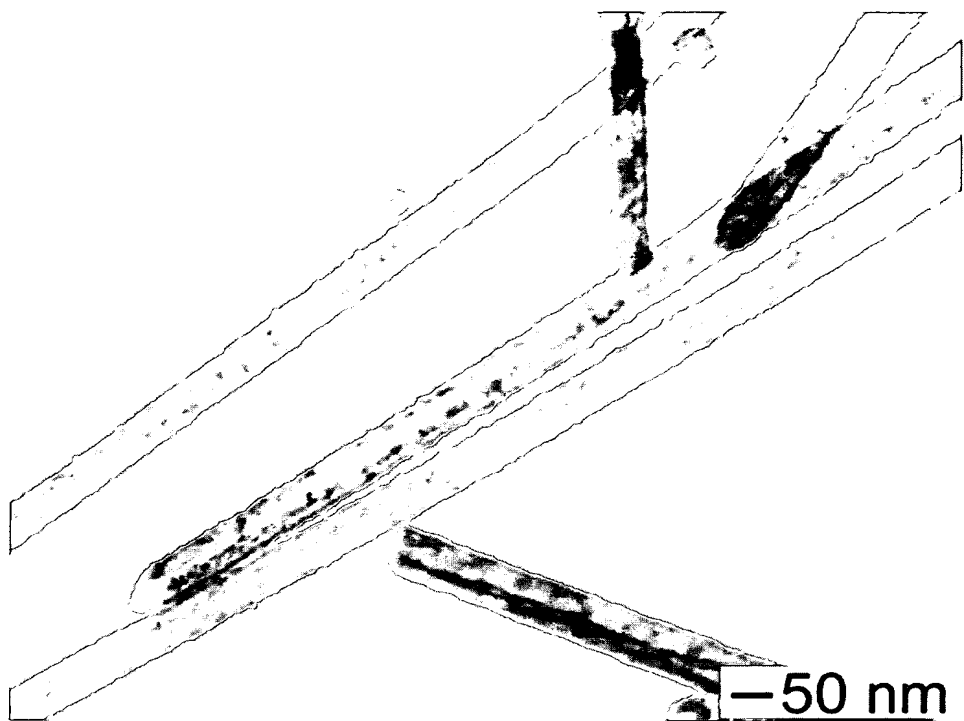
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*Fig. 13E*

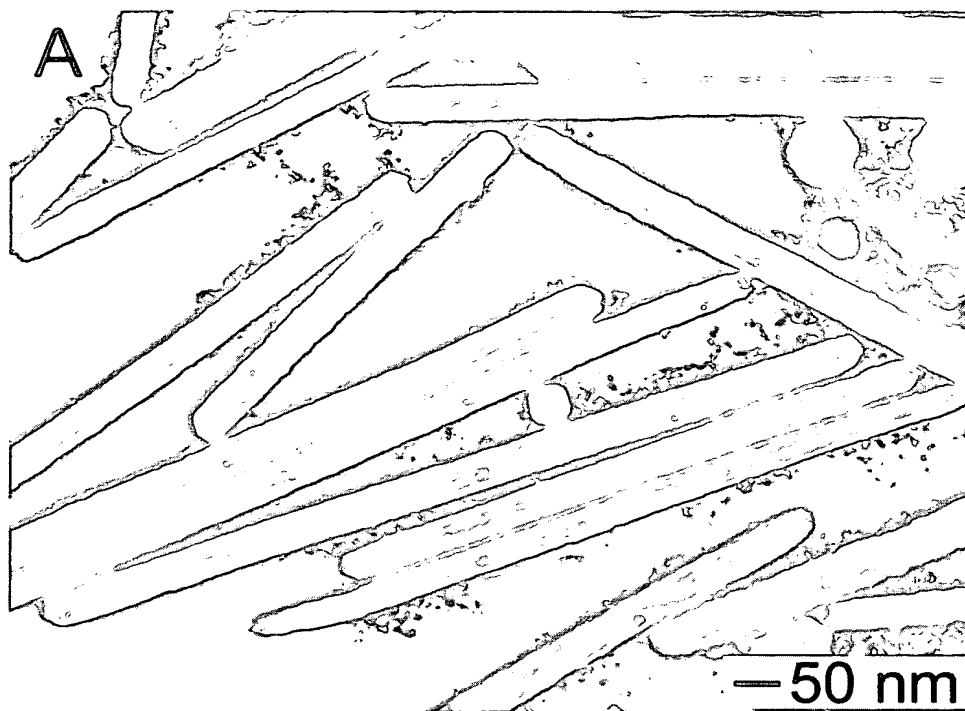


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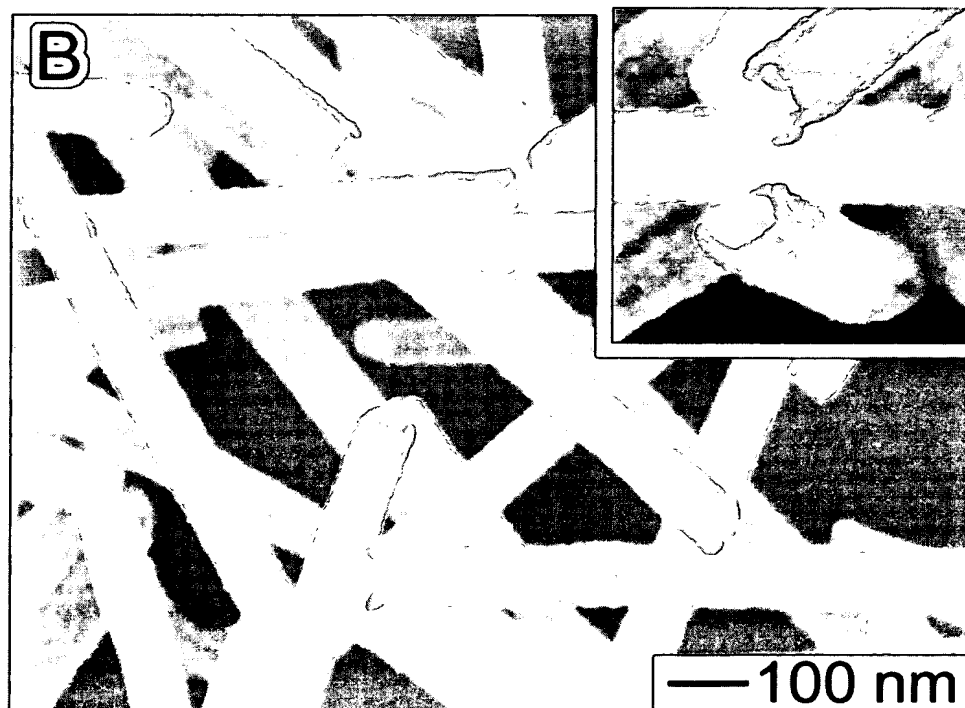
*Fig. 13F*



**Fig. 14**



*Fig. 15A*



*Fig. 15B*

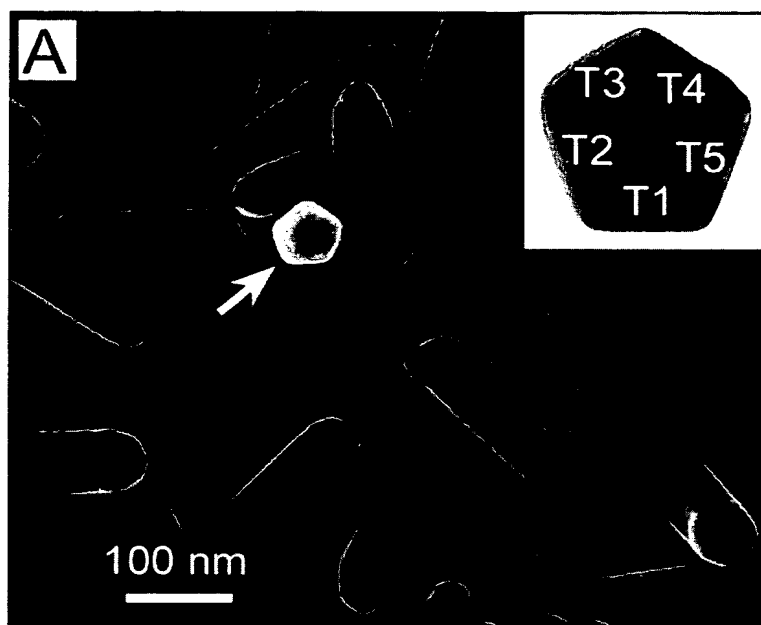


Fig. 16A

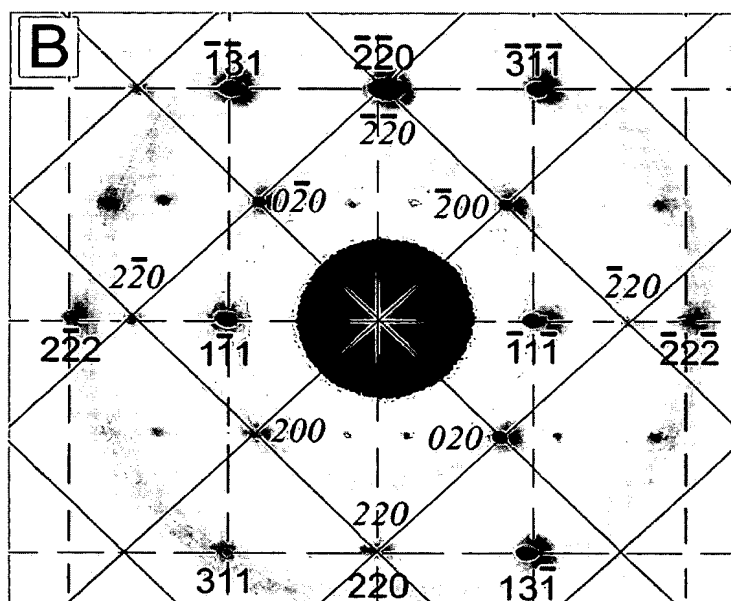
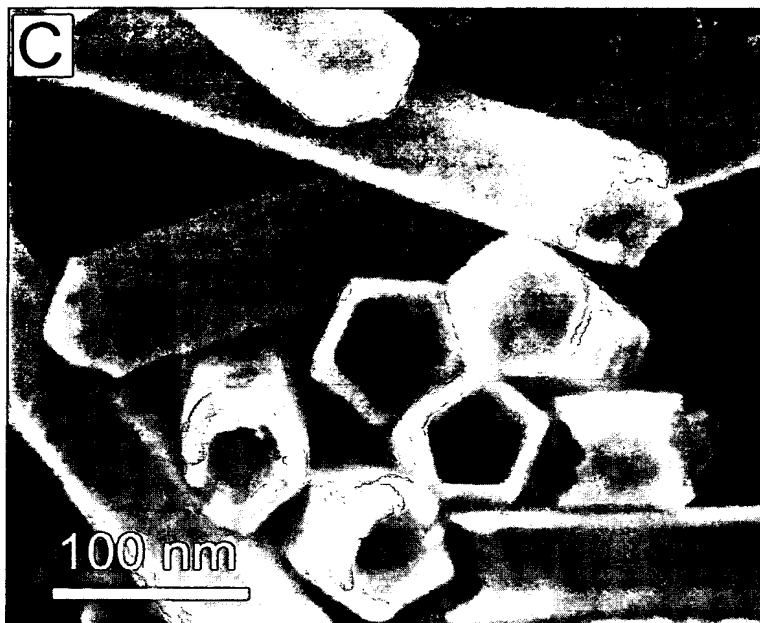
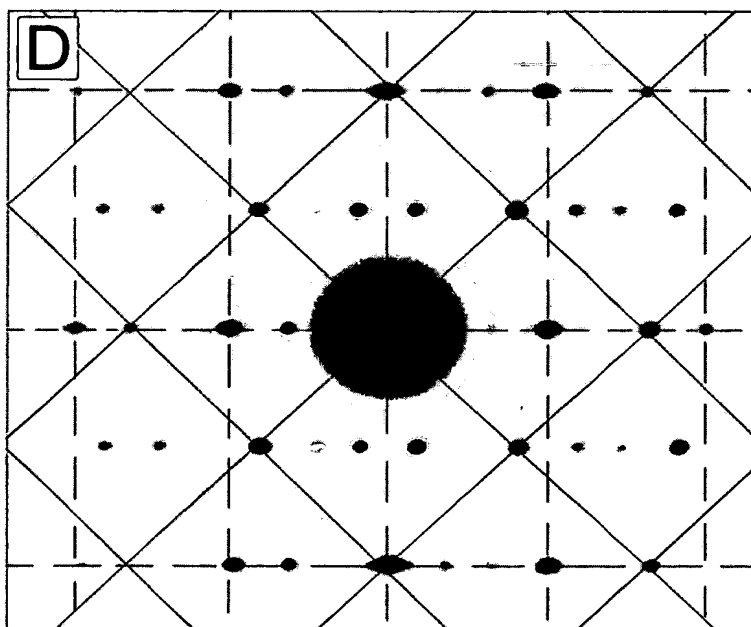


Fig. 16B



*Fig. 16C*



*Fig. 16D*



Fig. 16E

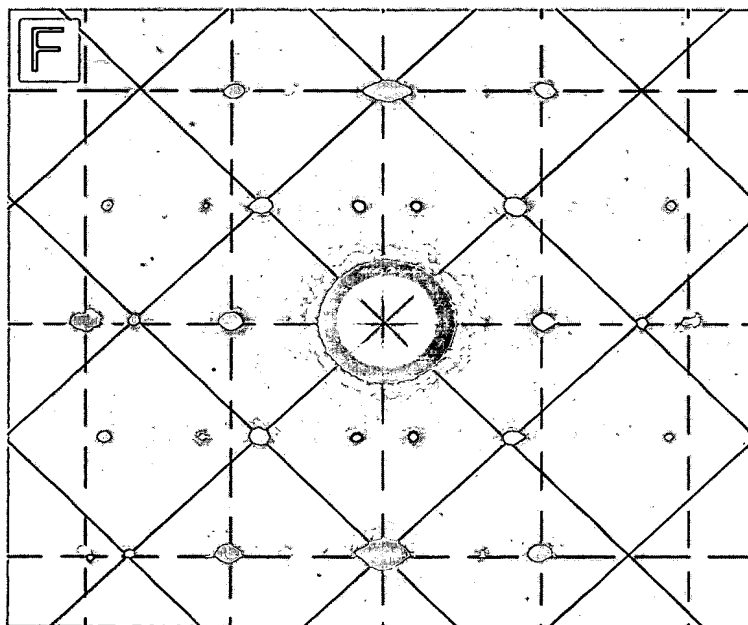
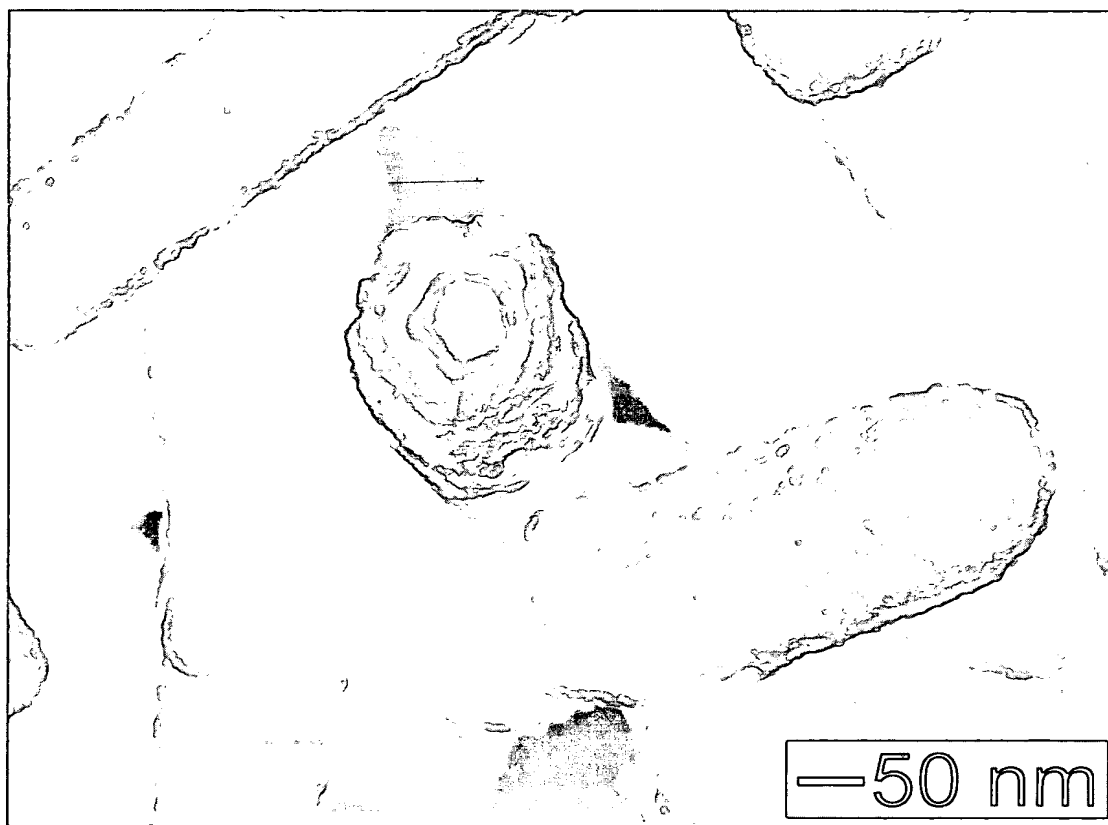


Fig. 16F



*Fig. 17*



*Fig. 18*



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REPLACEMENT SHEET (Set B)

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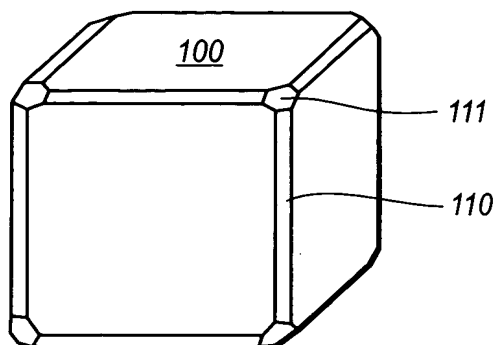


Fig. 1

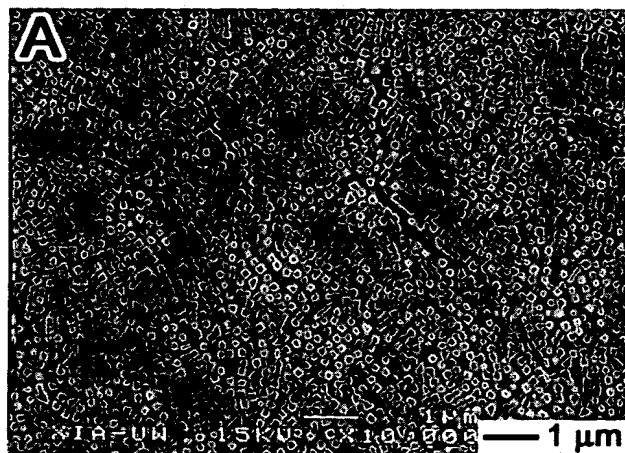


Fig. 2A

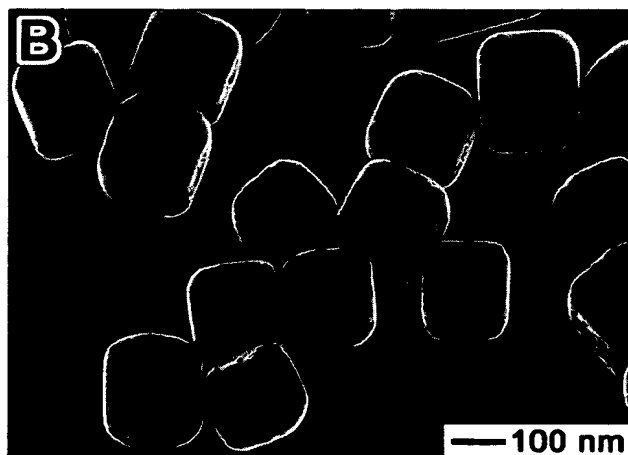
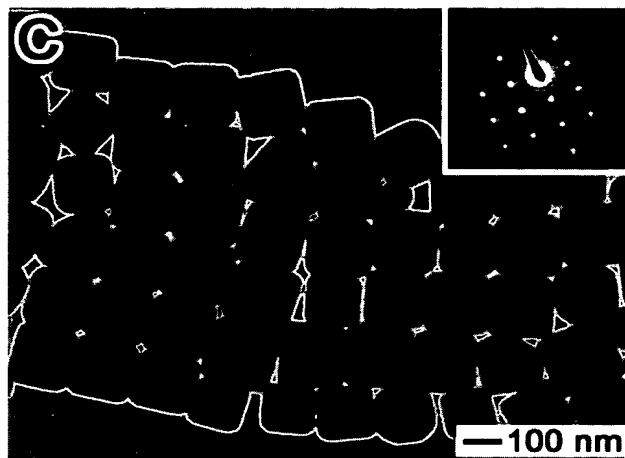
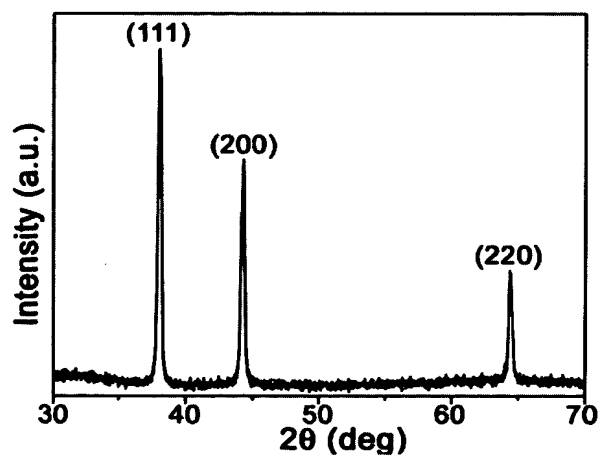


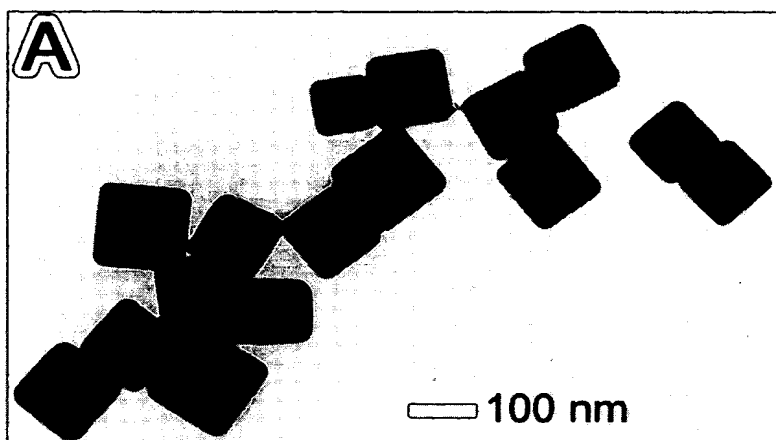
Fig. 2B



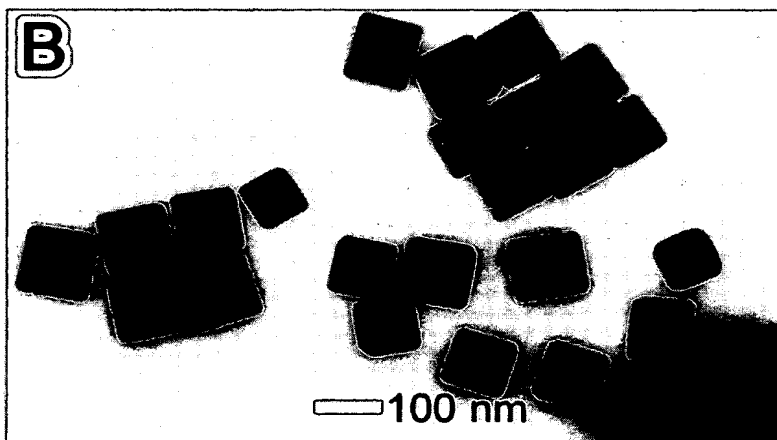
*Fig. 2C*



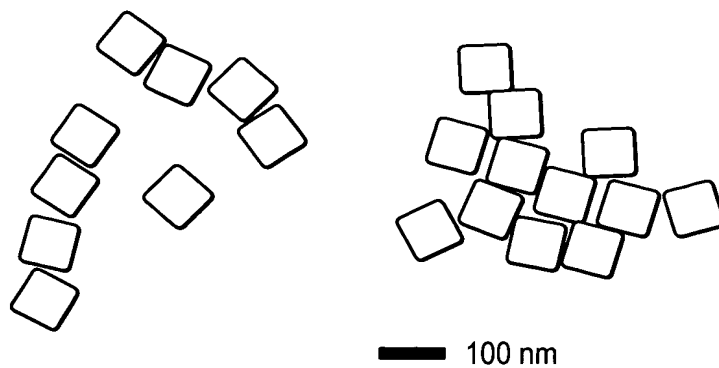
*Fig. 2D*



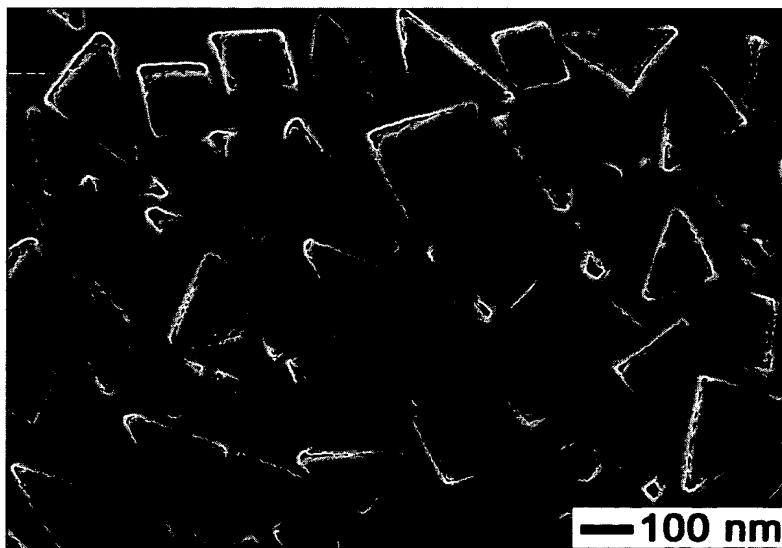
*Fig. 3A*



*Fig. 3B*

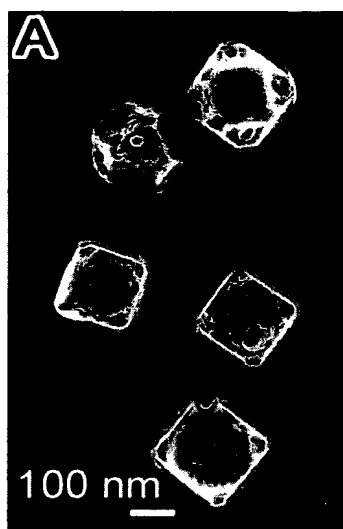


**Fig. 4**

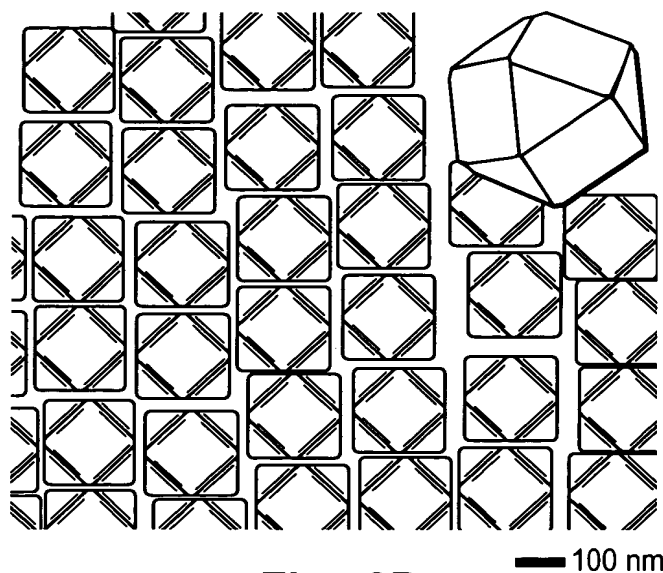


**Fig. 5**

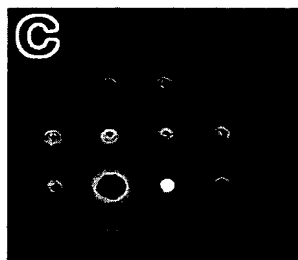
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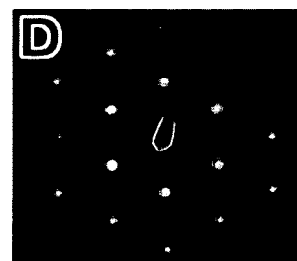
**Fig. 6A**



**Fig. 6B**



**Fig. 6C**



**Fig. 6D**

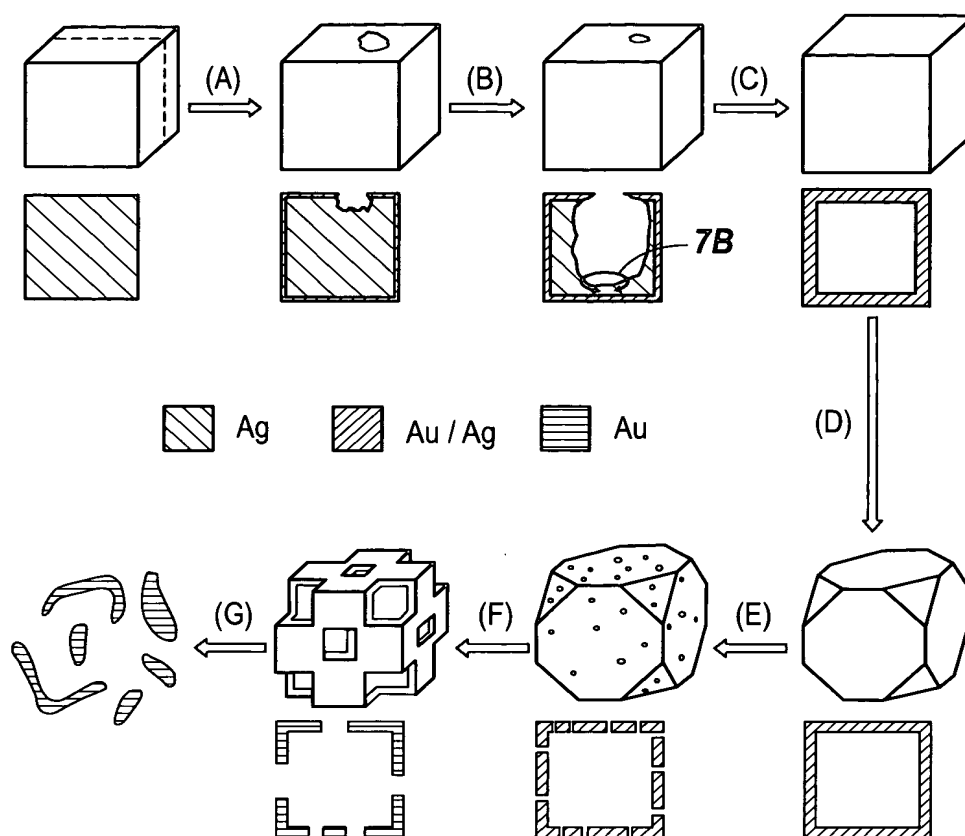


Fig. 7A

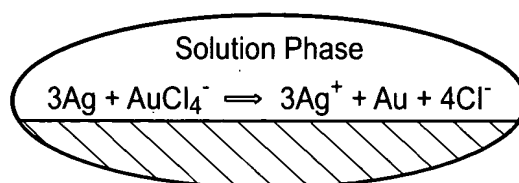


Fig. 7B

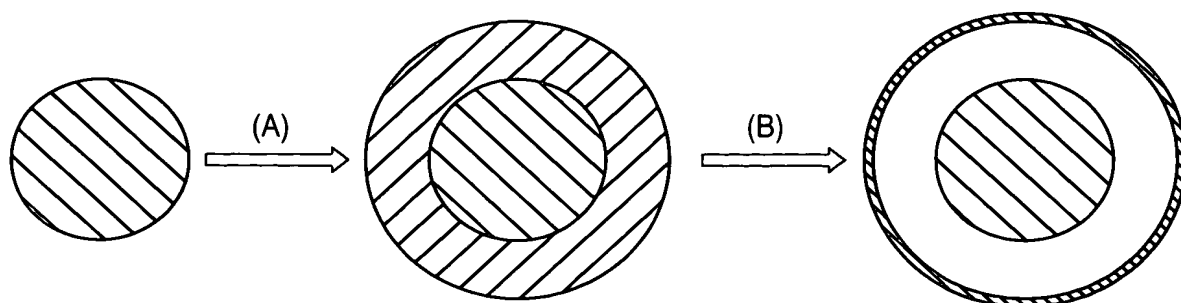
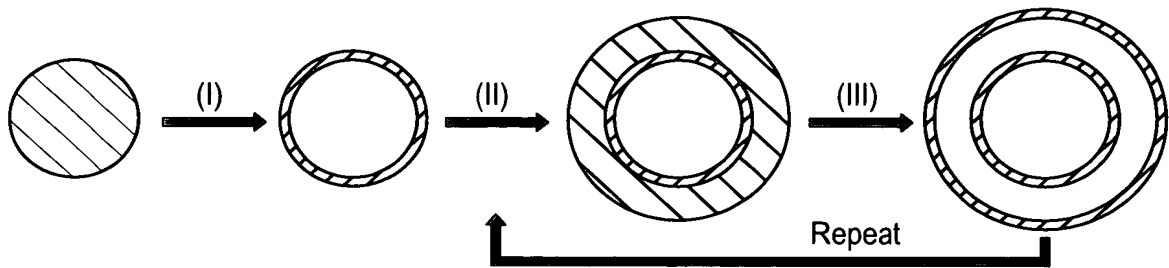
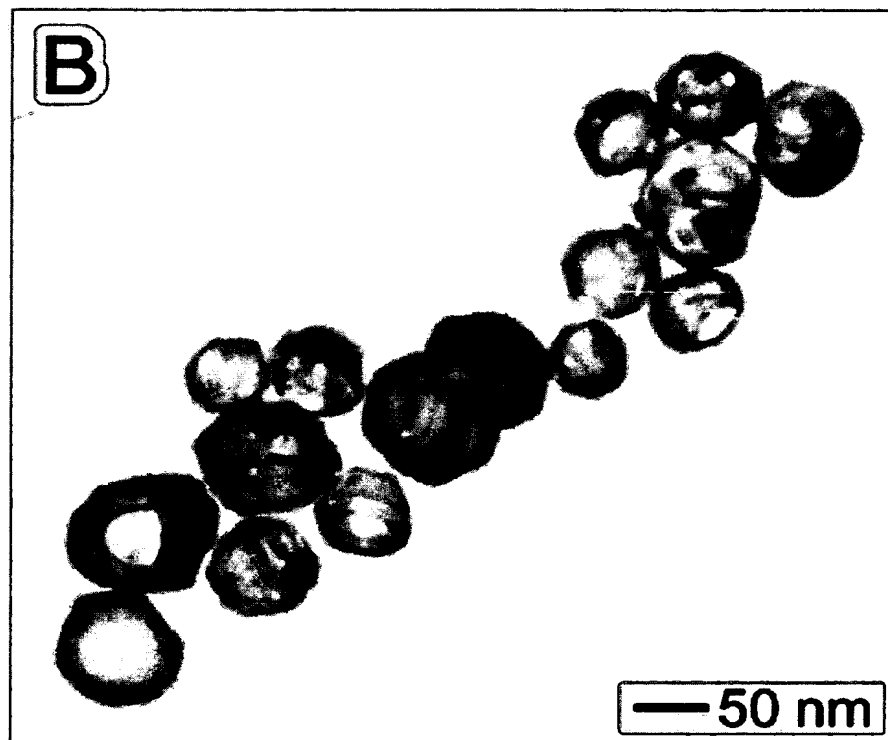


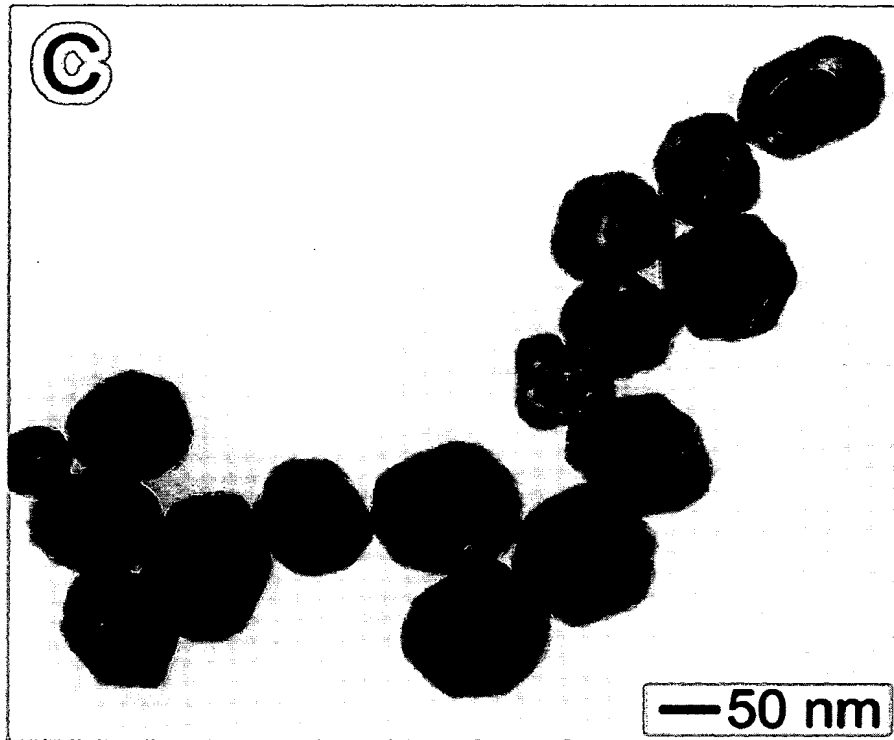
Fig. 8



**Fig. 9A**



**Fig. 9B**



*Fig. 9C*



*Fig. 9D*

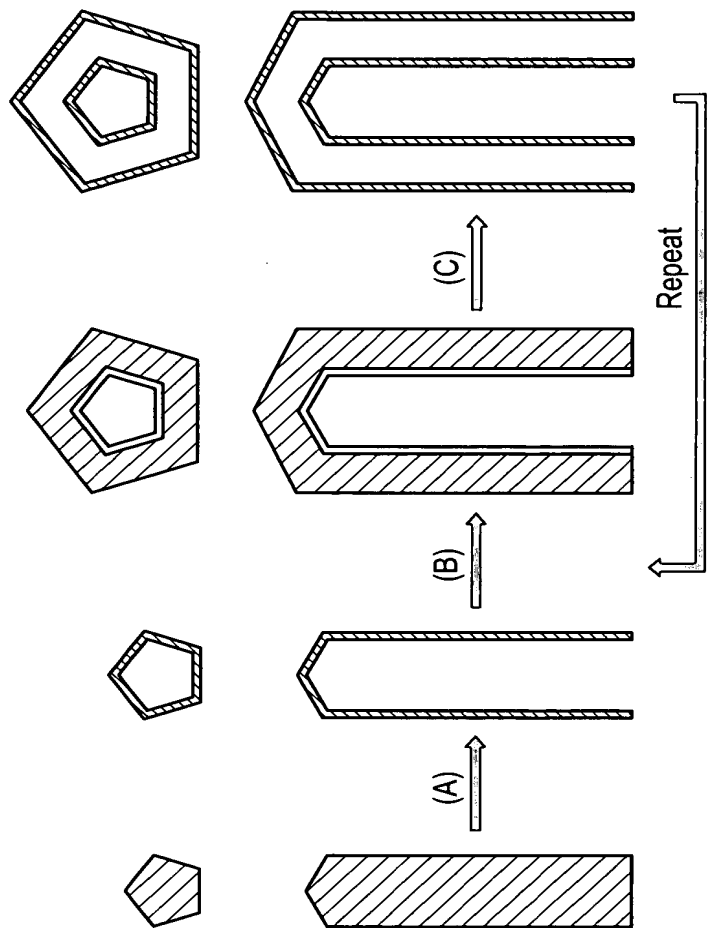
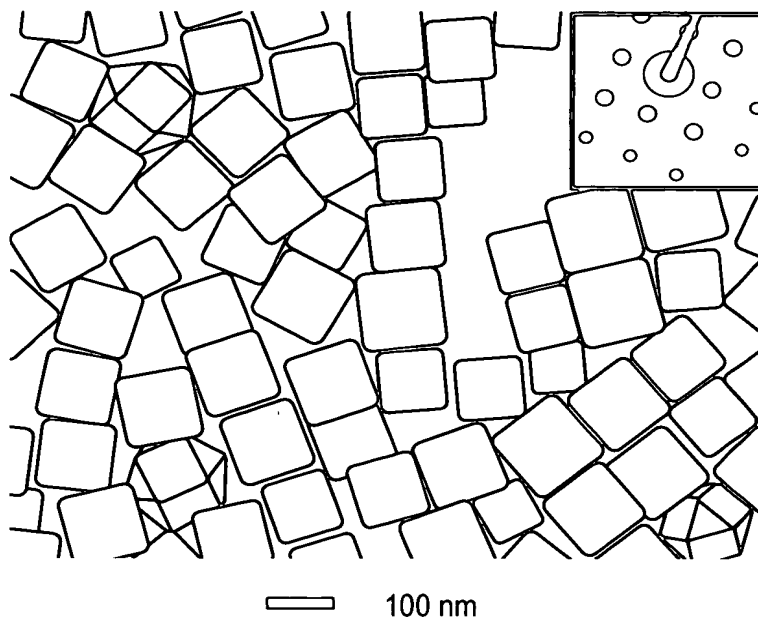
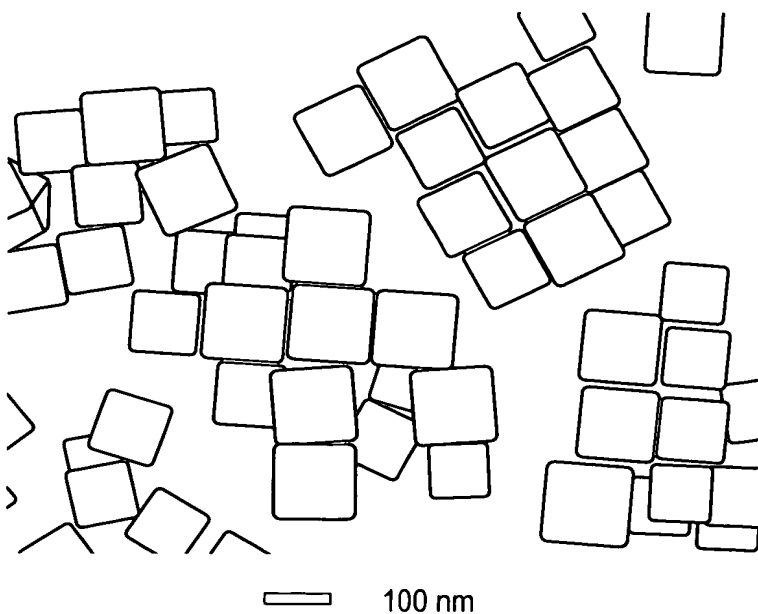


Fig. 10

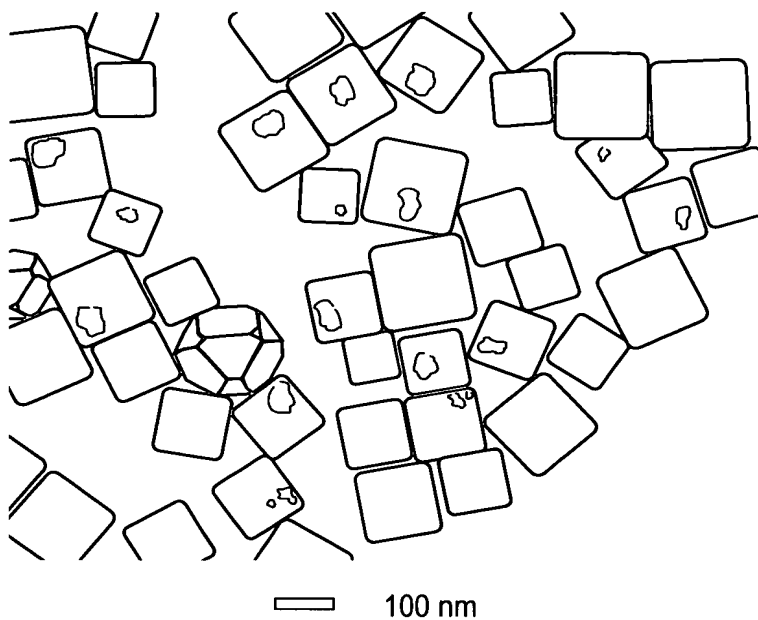
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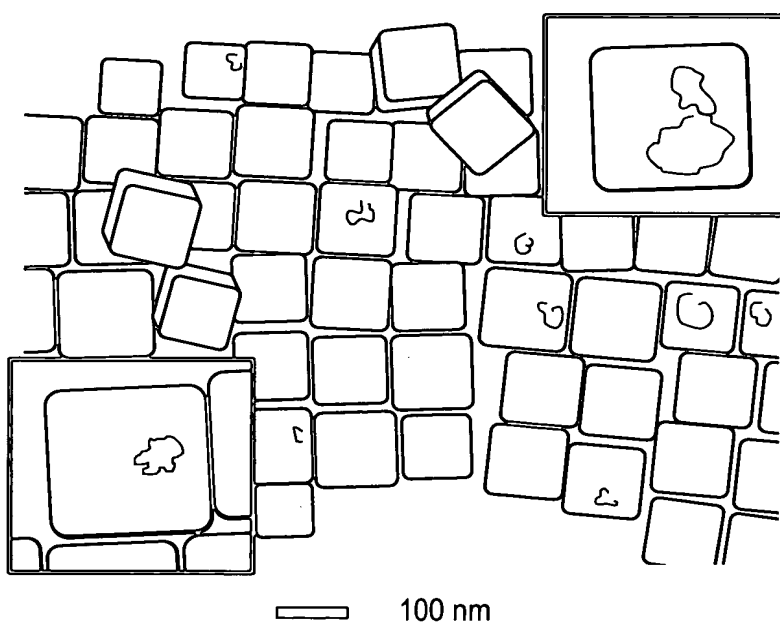
*Fig. 11A*



*Fig. 11B*

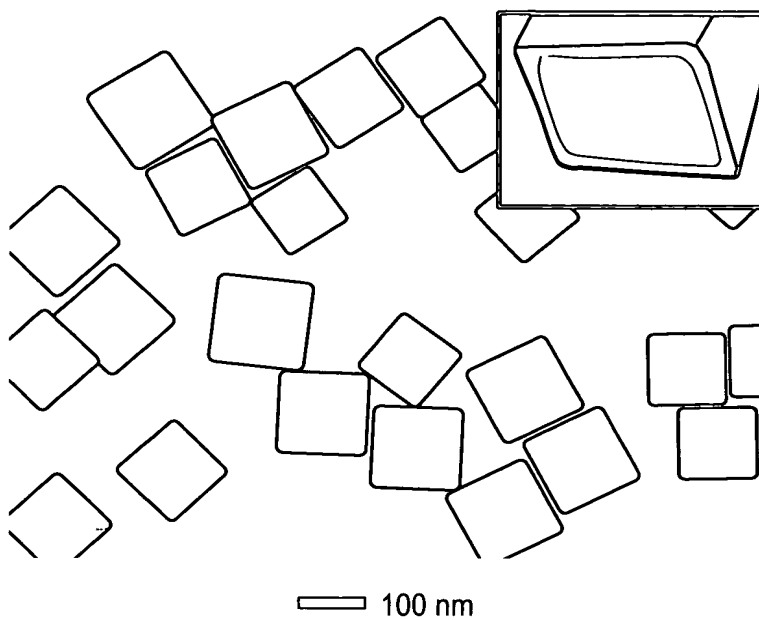


*Fig. 11C*

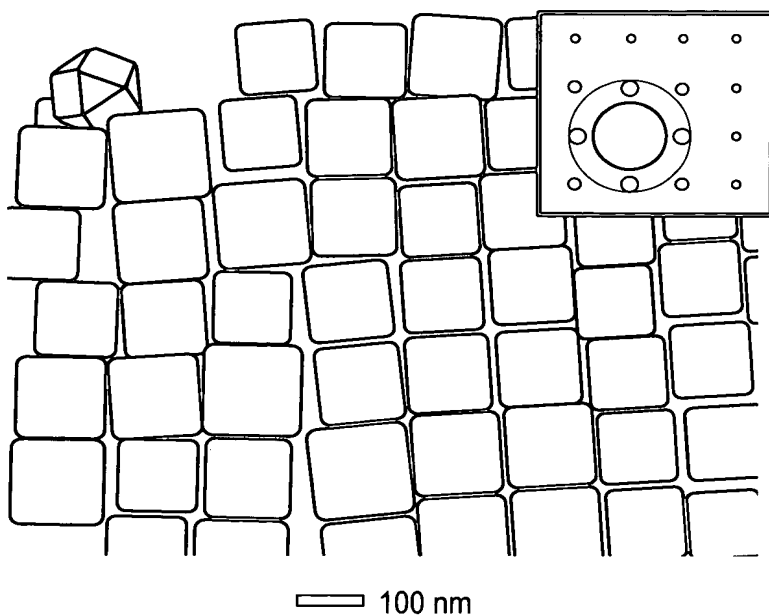


*Fig. 11D*

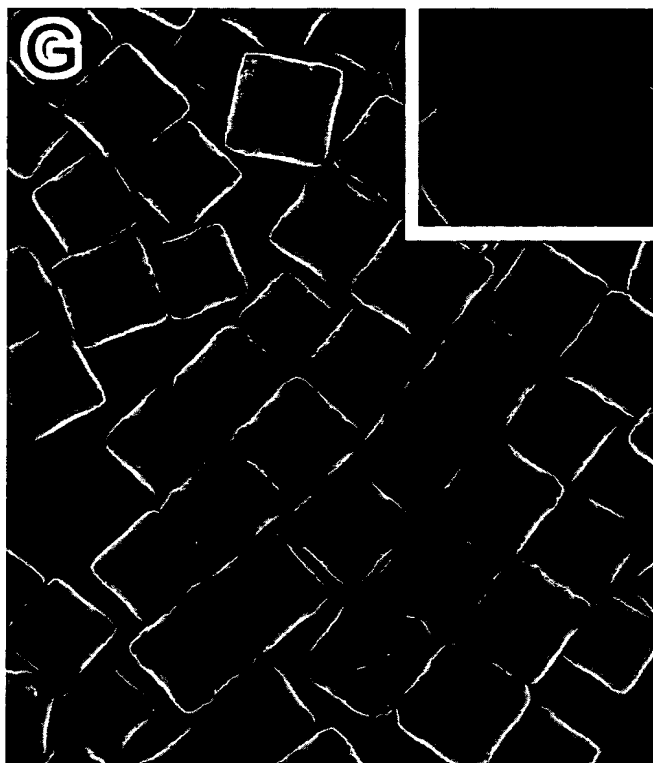
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*Fig. 11E*

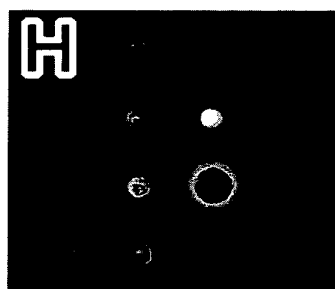


*Fig. 11F*



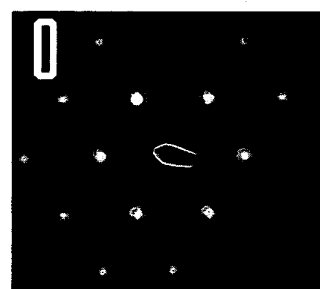
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*Fig. 11G*



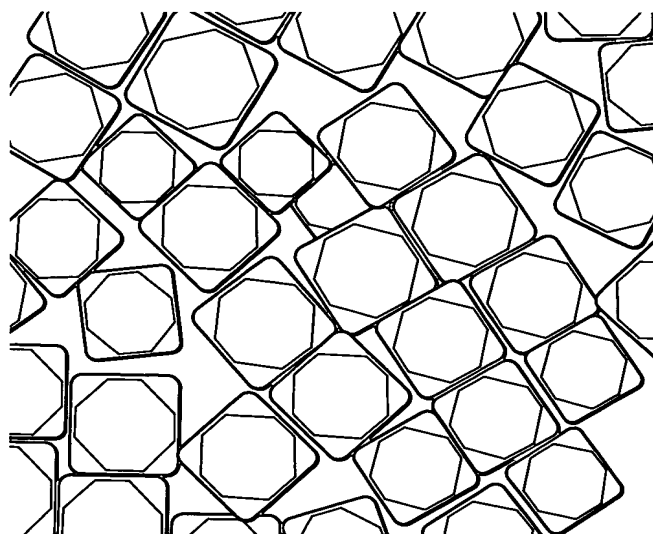
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*Fig. 11H*



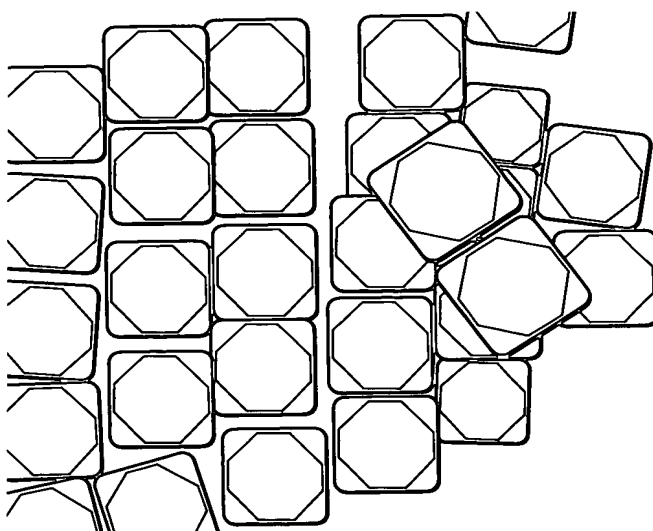
—100 nm

*Fig. 11I*



— 100 nm

*Fig. 11J*



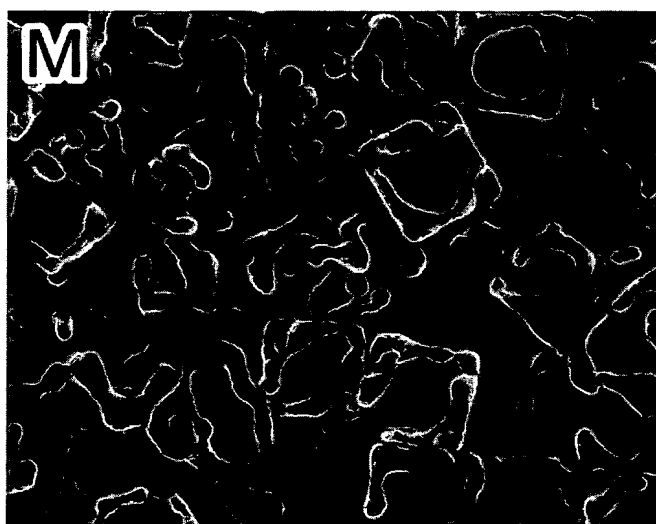
— 100 nm

*Fig. 11K*



—100 nm

*Fig. 11L*



—100 nm

*Fig. 11M*

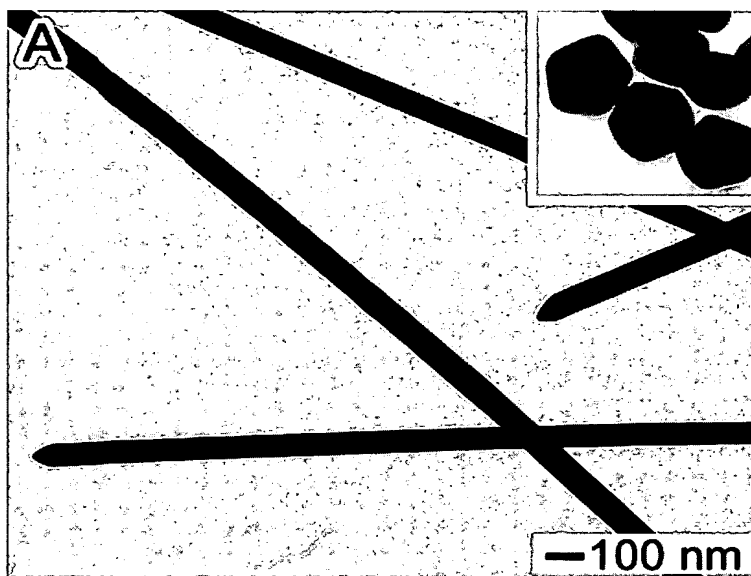


Fig. 12A

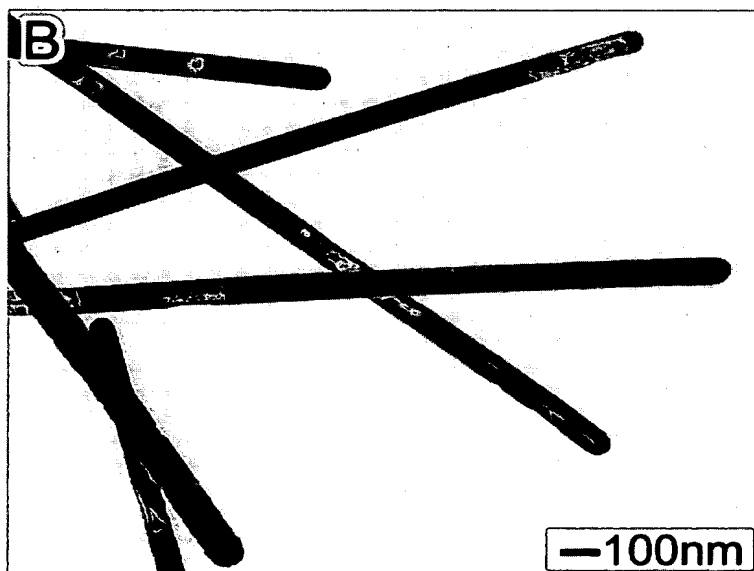
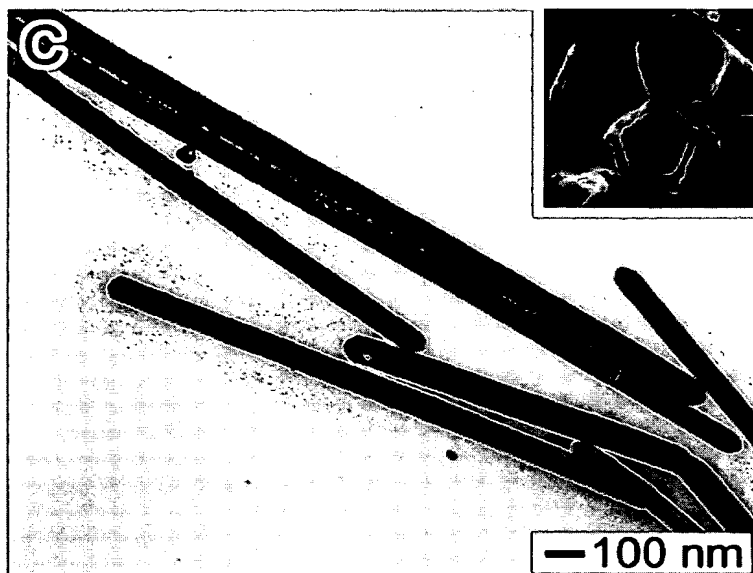
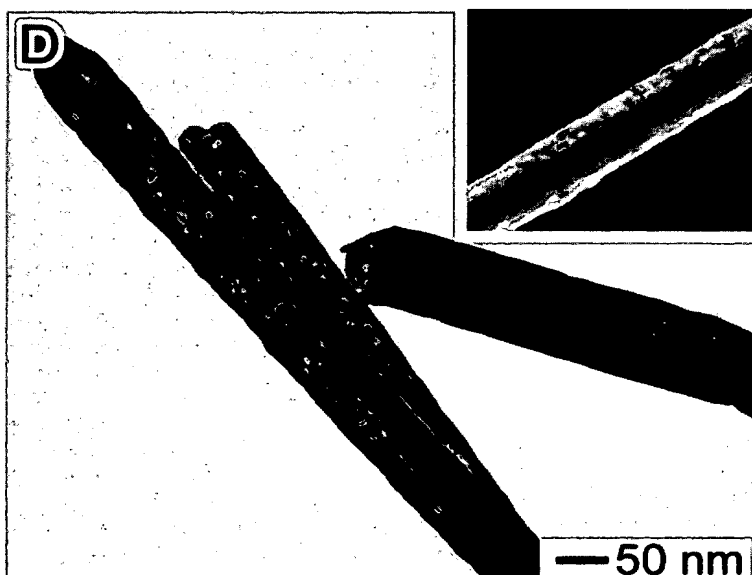


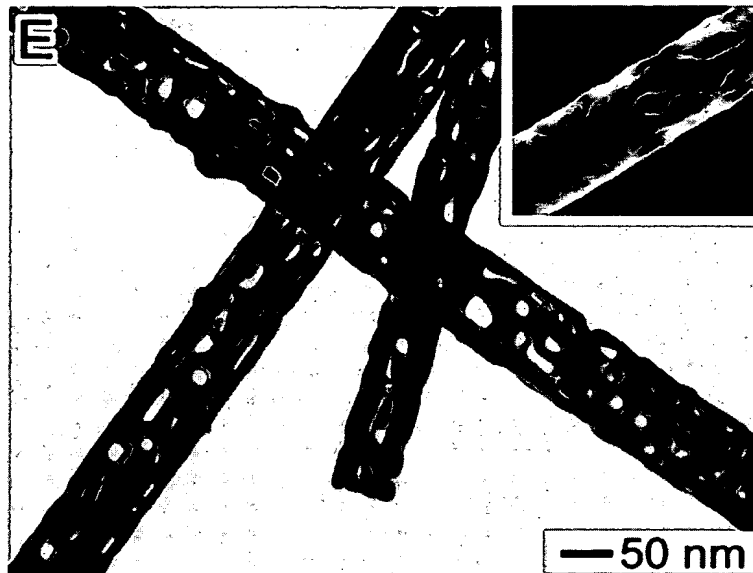
Fig. 12B



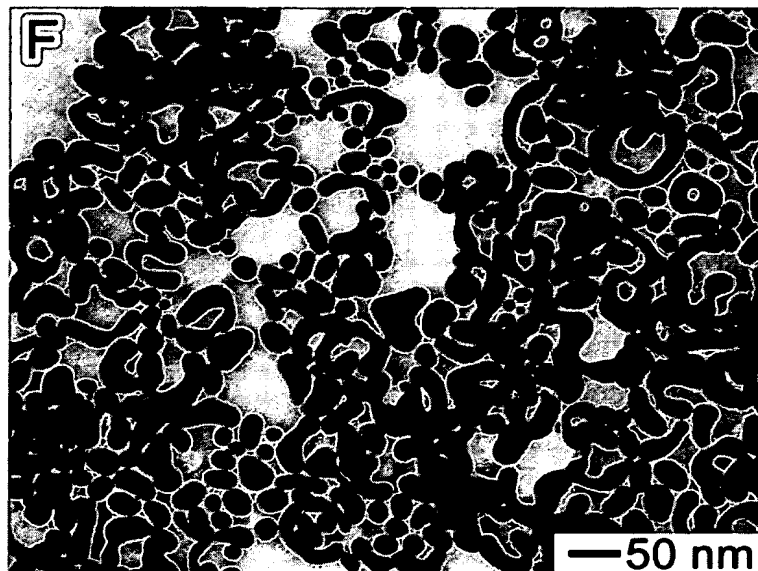
*Fig. 12C*



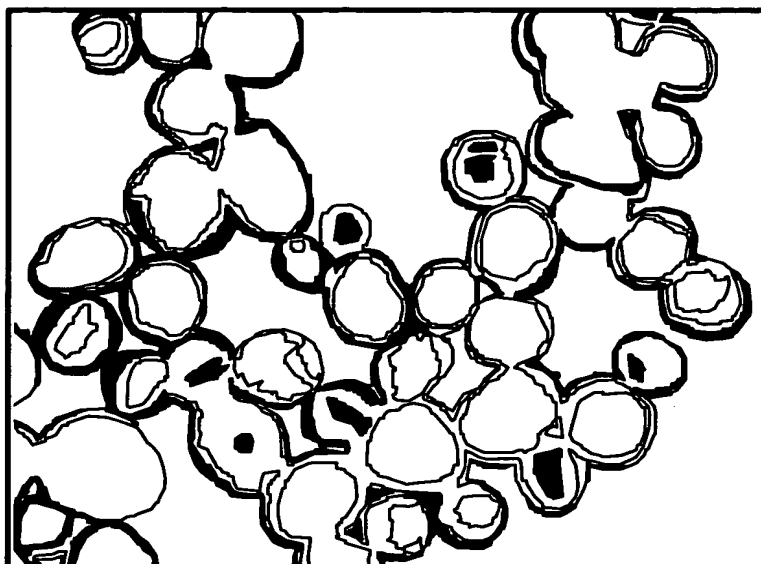
*Fig. 12D*



*Fig. 12E*

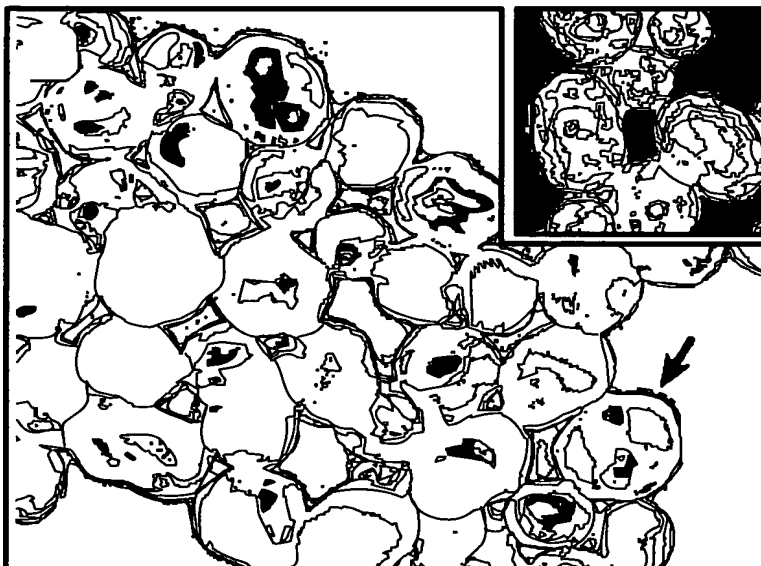


*Fig. 12F*



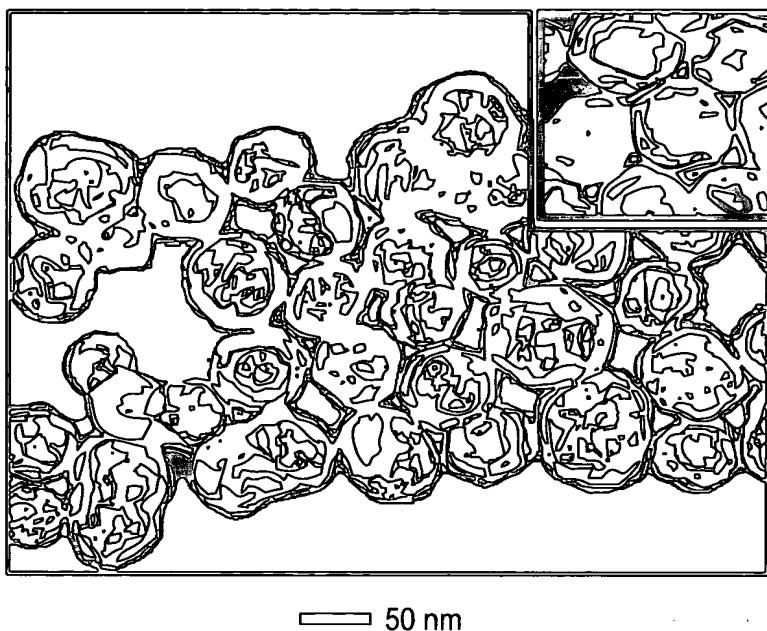
— 50 nm

**Fig. 13A**

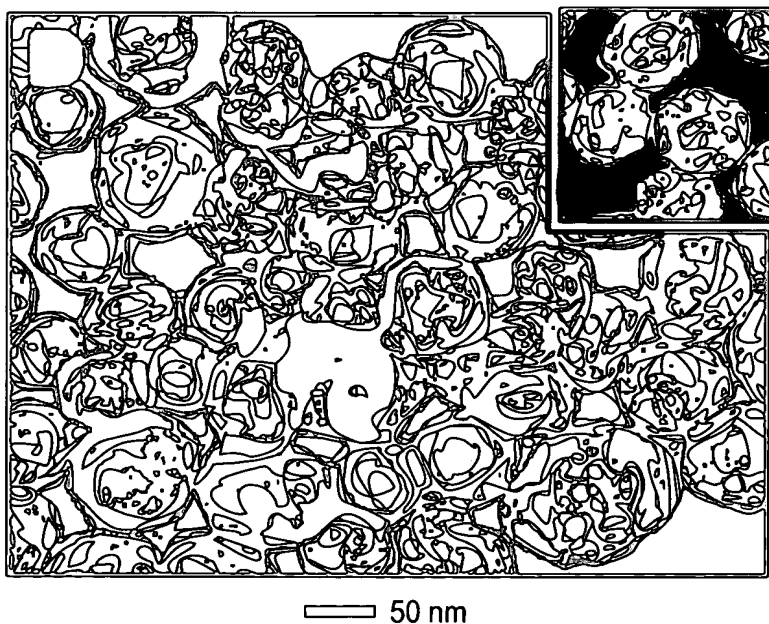


— 50 nm

**Fig. 13B**



*Fig. 13C*

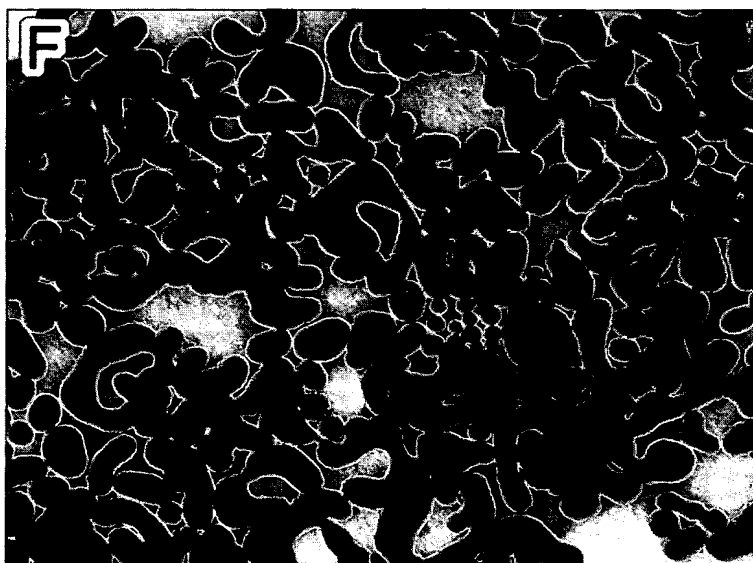


*Fig. 13D*



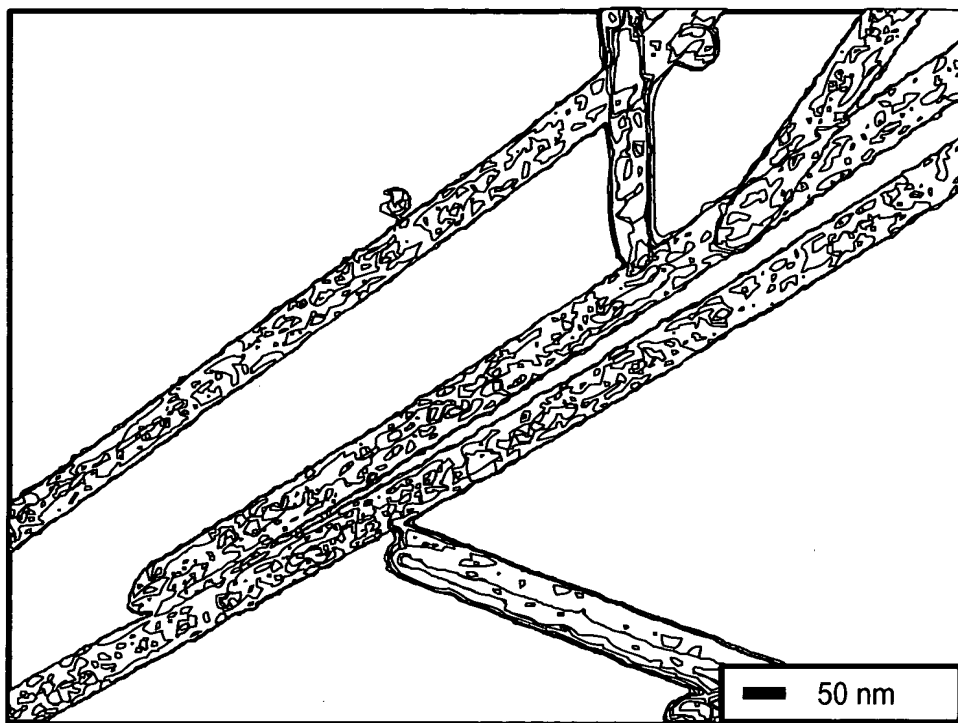
— 50 nm

*Fig. 13E*

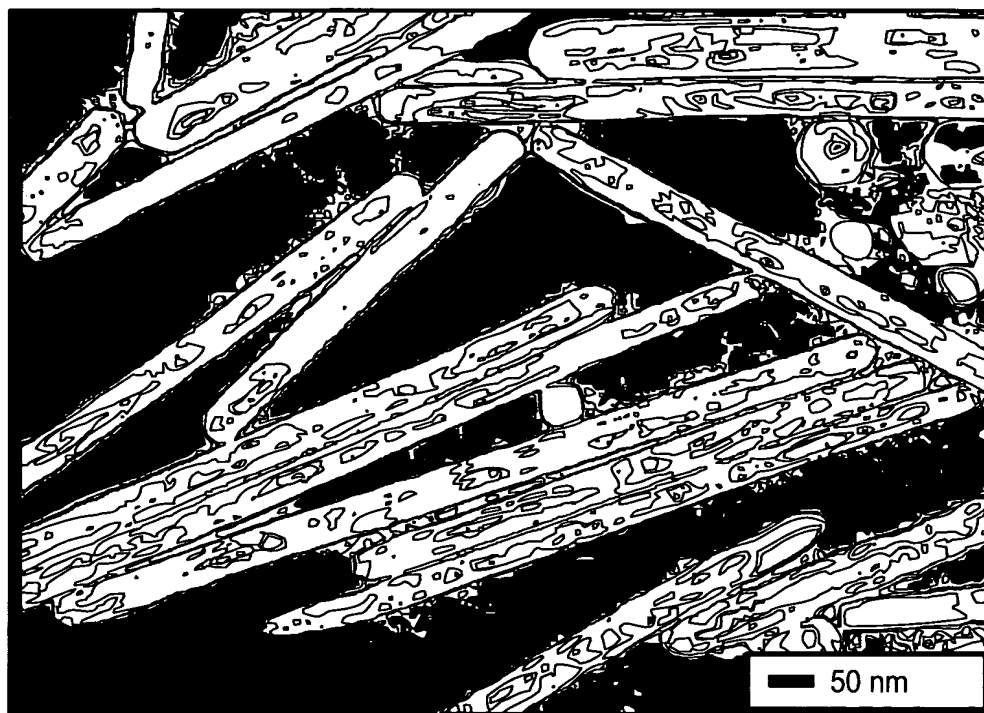


— 50 nm

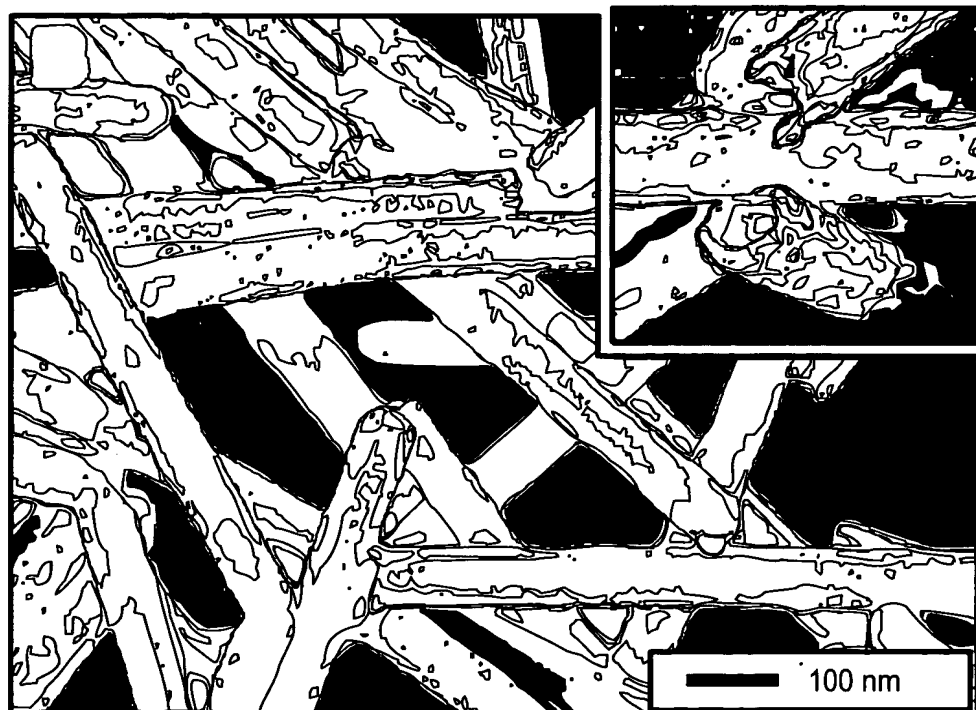
*Fig. 13F*



**Fig. 14**



**Fig. 15A**



**Fig. 15B**

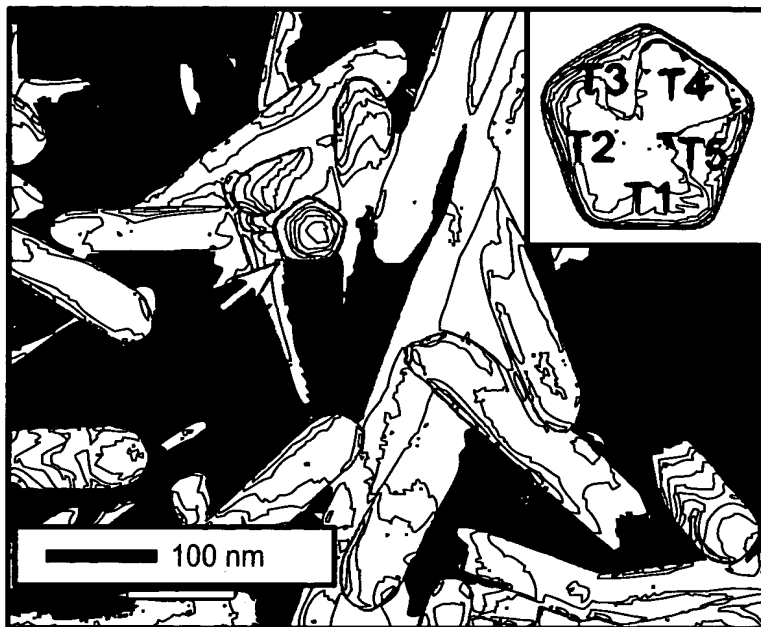


Fig. 16A

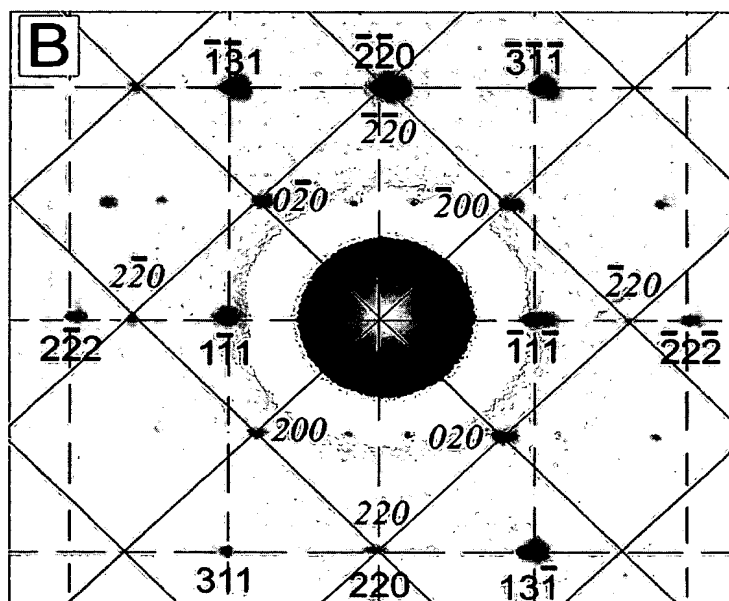
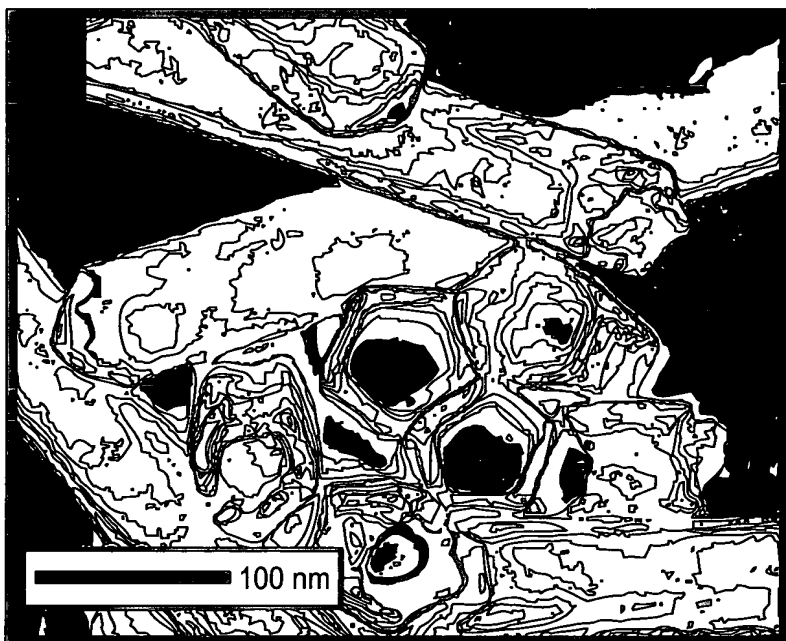
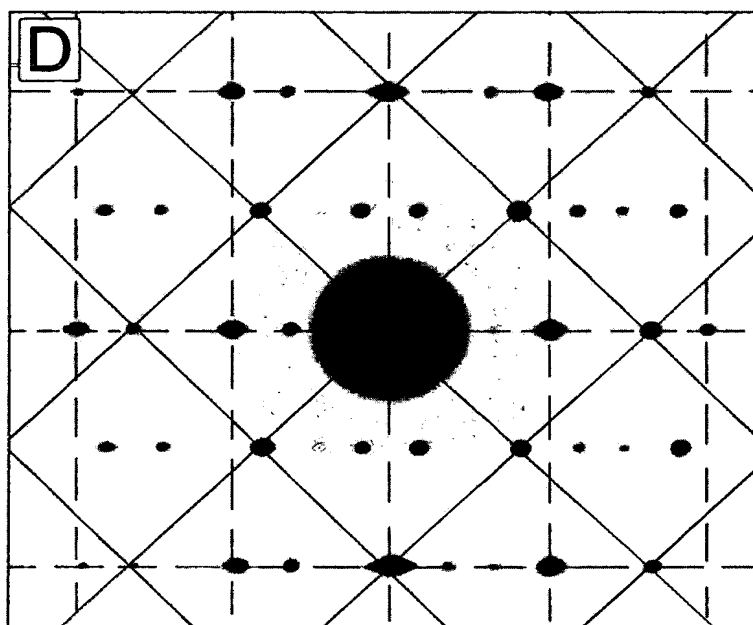


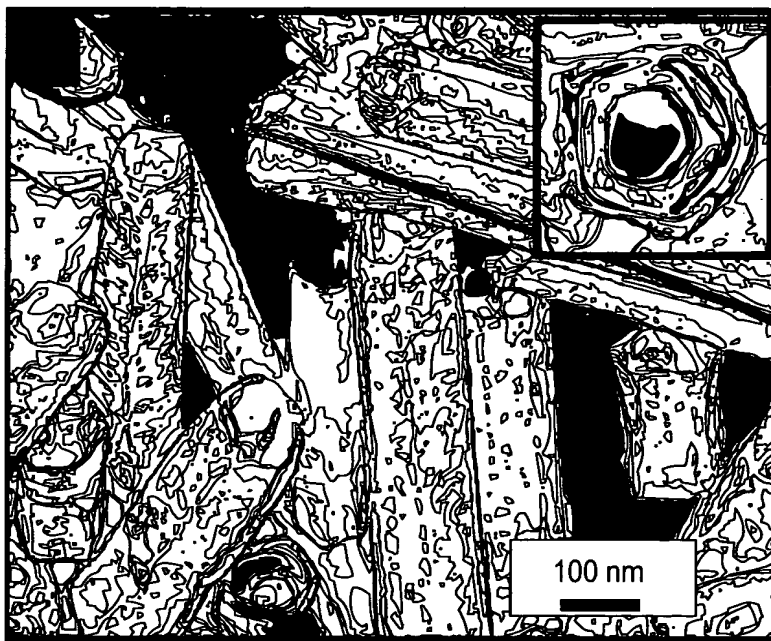
Fig. 16B



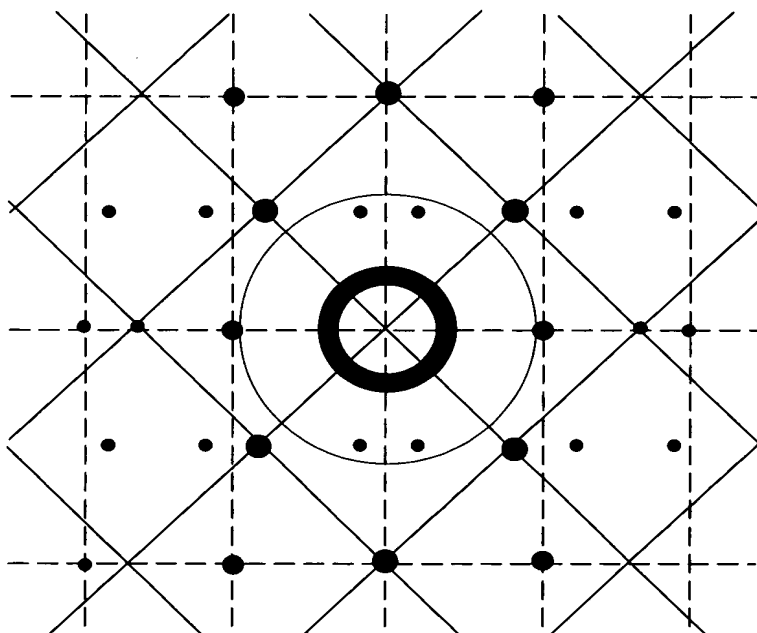
*Fig. 16C*



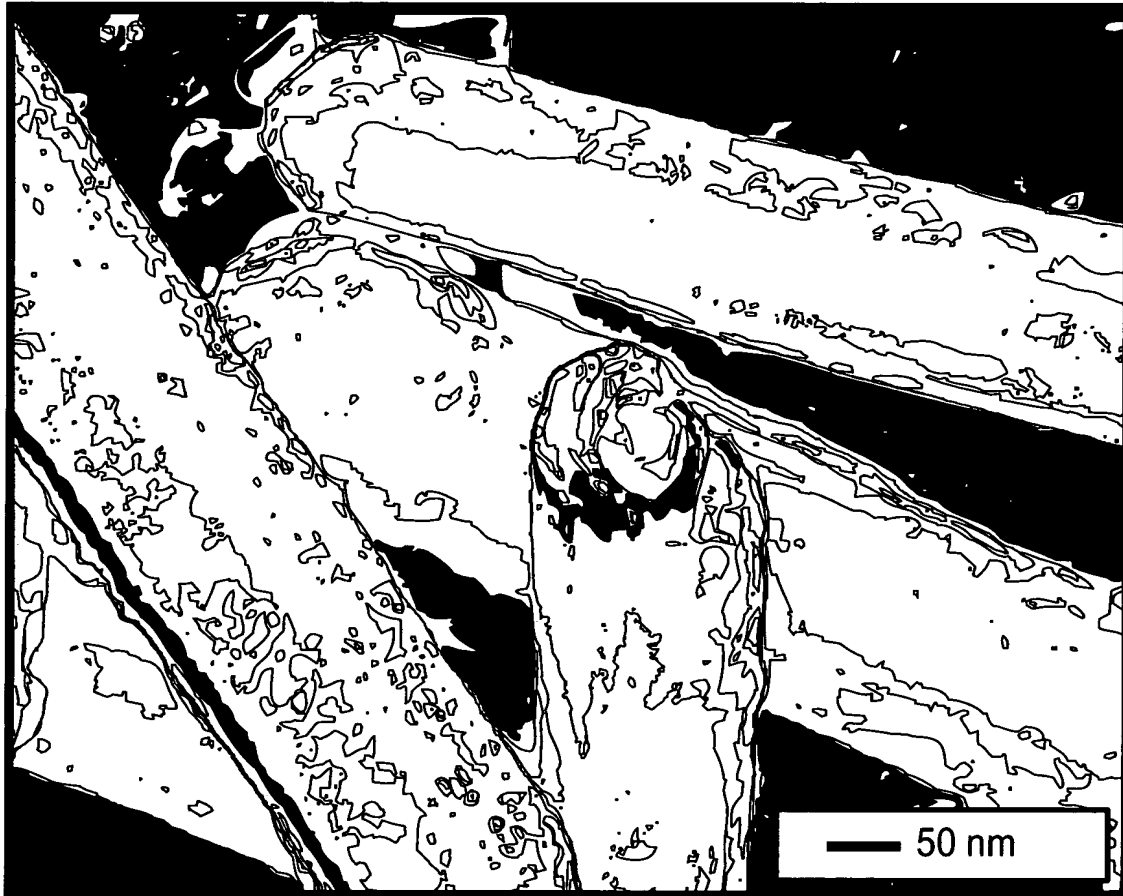
*Fig. 16D*



**Fig. 16E**



**Fig. 16F**



**Fig. 17**



*Fig. 18*

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